

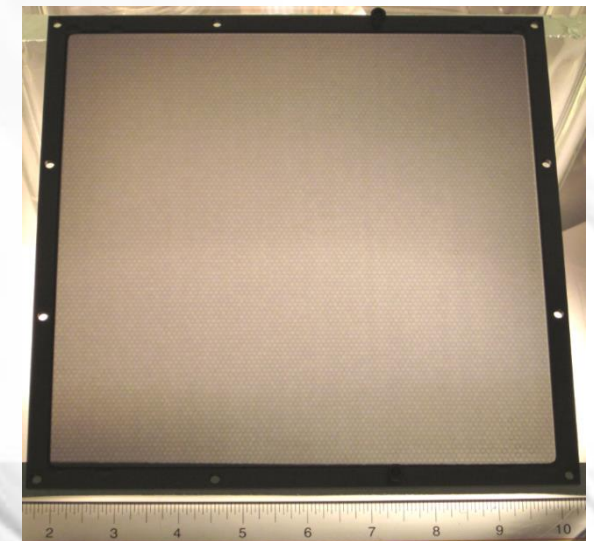
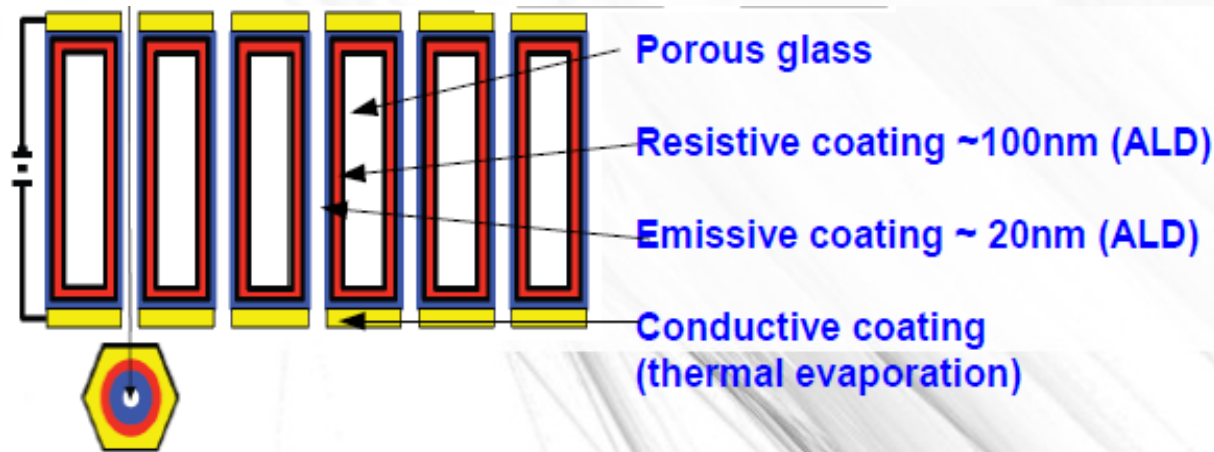
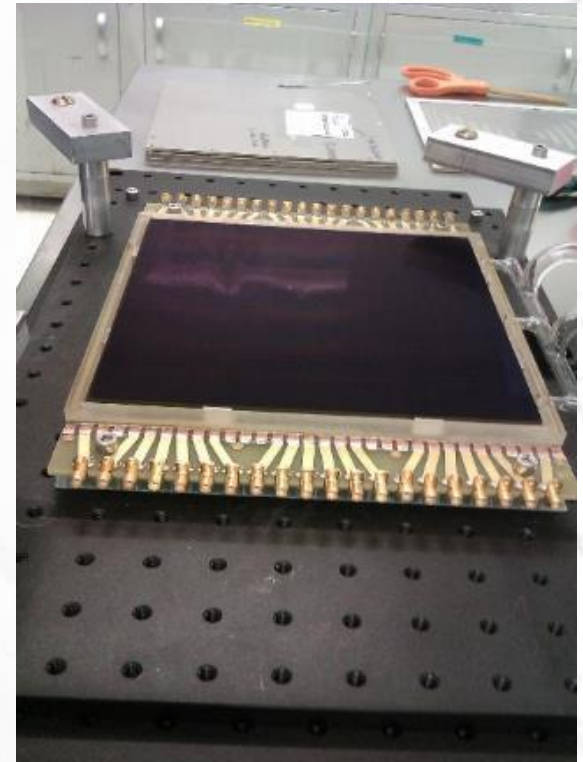
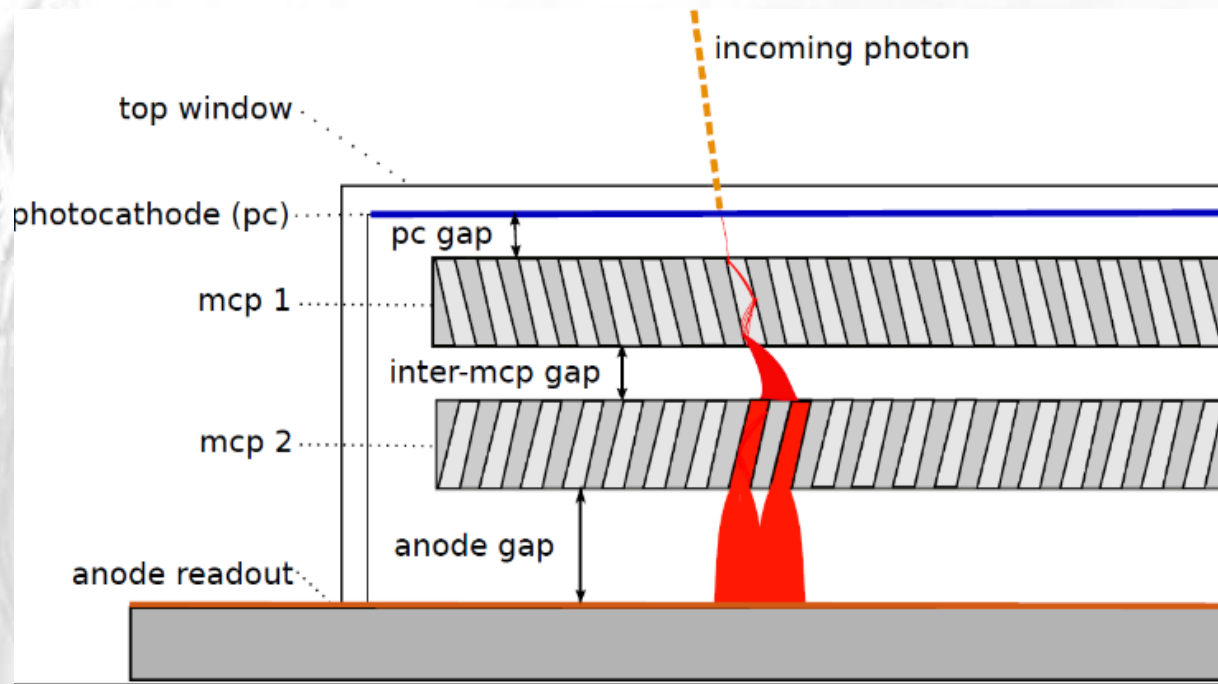
Large-Area Picosecond Photo-Detectors

Andrey Elagin
University of Chicago

Outline

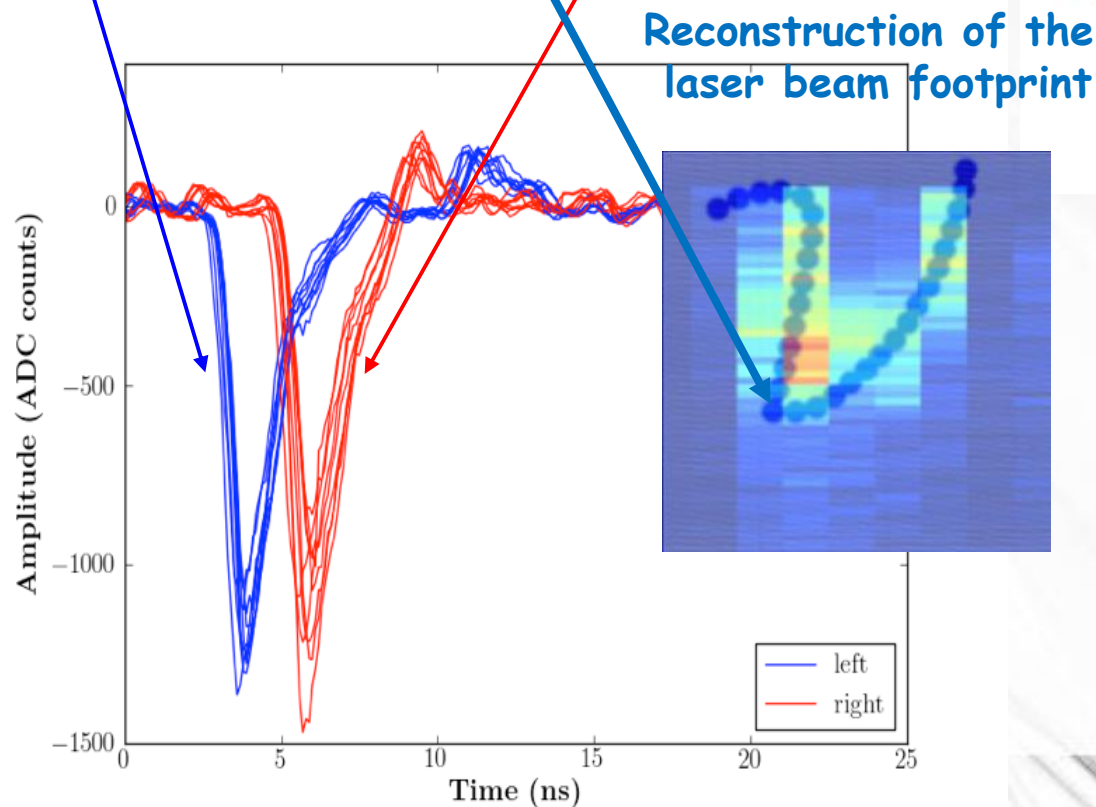
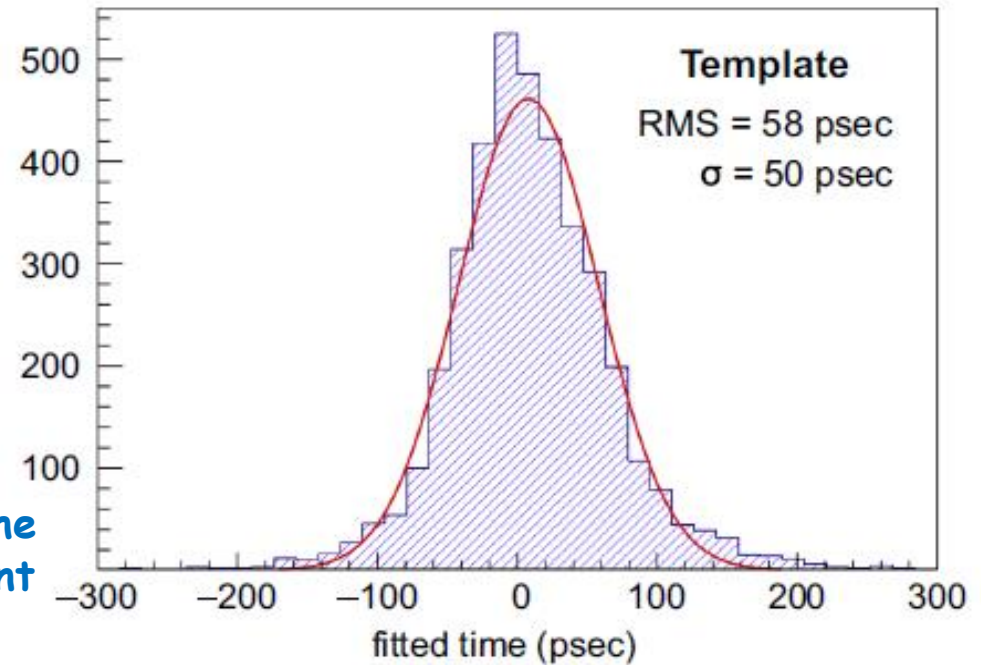
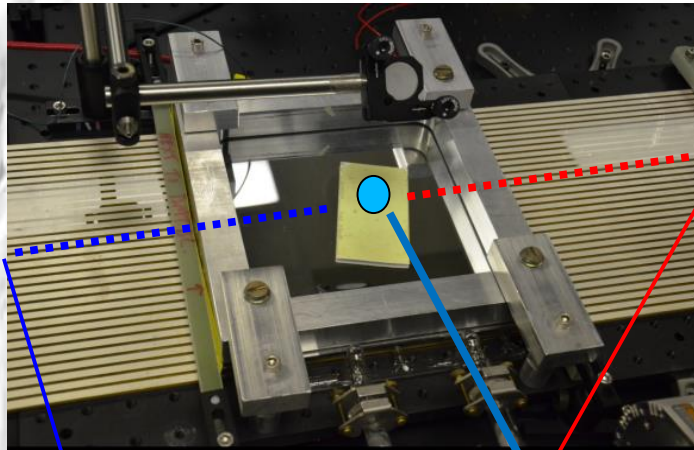
- LAPPD Overview
- Commercialization status at Incom Inc.
- R&D Towards Volume Production
 - development of in-situ assembly process at UChicago
 - Gen-II LAPPD

LAPPD



LAPPD Prototype Testing Results

Single PE resolution



Demonstrated characteristics:
single PE timing ~ 50 ps
multi PE timing ~ 35 ps
differential timing ~ 5 ps
position resolution < 1 mm
gain $> 10^7$

RSI 84, 061301 (2013),
NIMA 732, (2013) 392
NIMA 795, (2015) 1

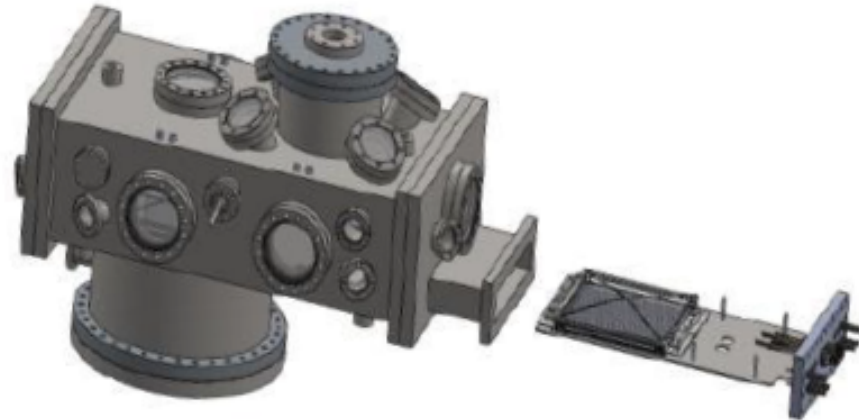
See [arXiv:1603.01843](https://arxiv.org/abs/1603.01843)
for a complete LAPPD bibliography

Commercialization Status

Incom V2.0 LAPPD Integration & Sealing Process & Hardware

Process:

- UHV - with Conflat seals, scroll, turbo and ion pump.
- Tile kit components pre-assembled & locked in place .
- Baked @ 350C to low 10^{-10} torr range
- In-tank scrubbing
- Window Transfer Process
- Na_2KSb Photocathode deposition @ 190C using SAES beads.
- Hot Indium Seal - with grooved sidewalls

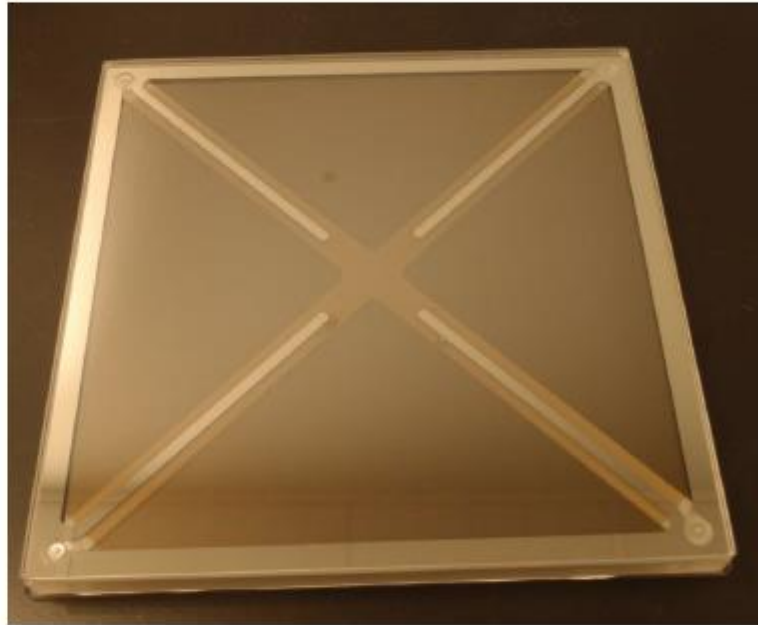
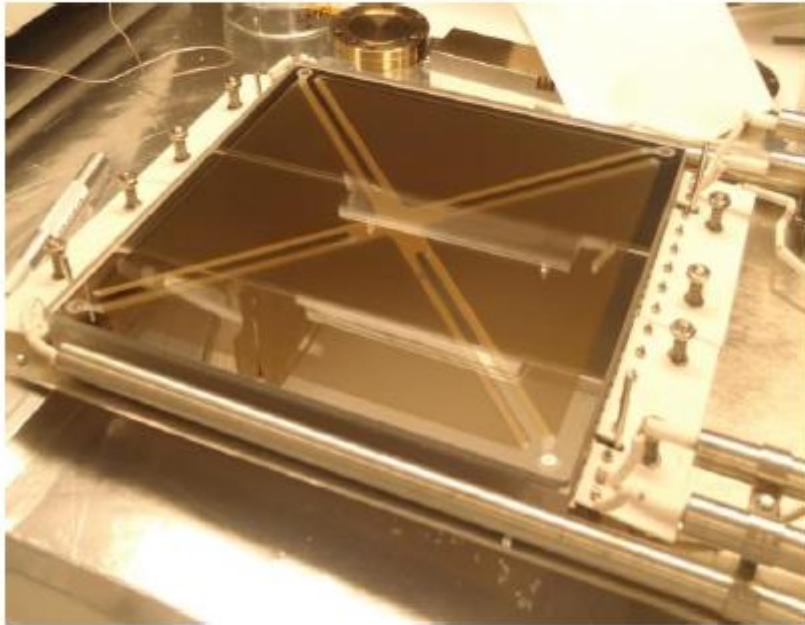


Hardware:

- Single "Fully Bakeable" Chamber: 30"L X 16"W X 8"H
- Simple window transfer between photocathode deposition & sealing.
- Electrical interconnects for in-process monitoring
- Readily expandable for volume production

Commercialization Status

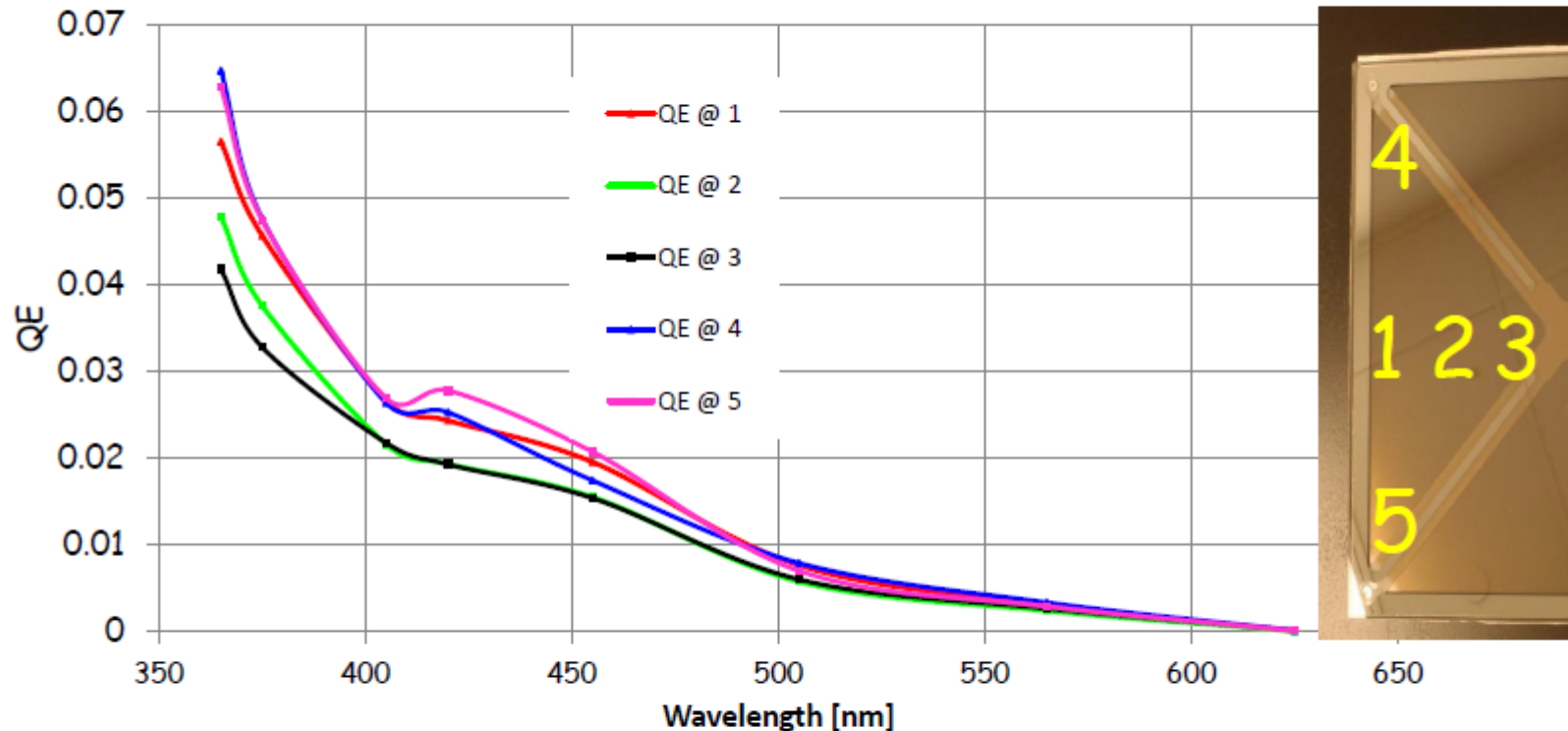
LAPPD #10 @STP



- LAPPD #10 Sealed, October 11, 2016
- No color change in PC upon venting UHV tank to STP
- Window deflection, characteristic of tile under vacuum.

Commercialization Status

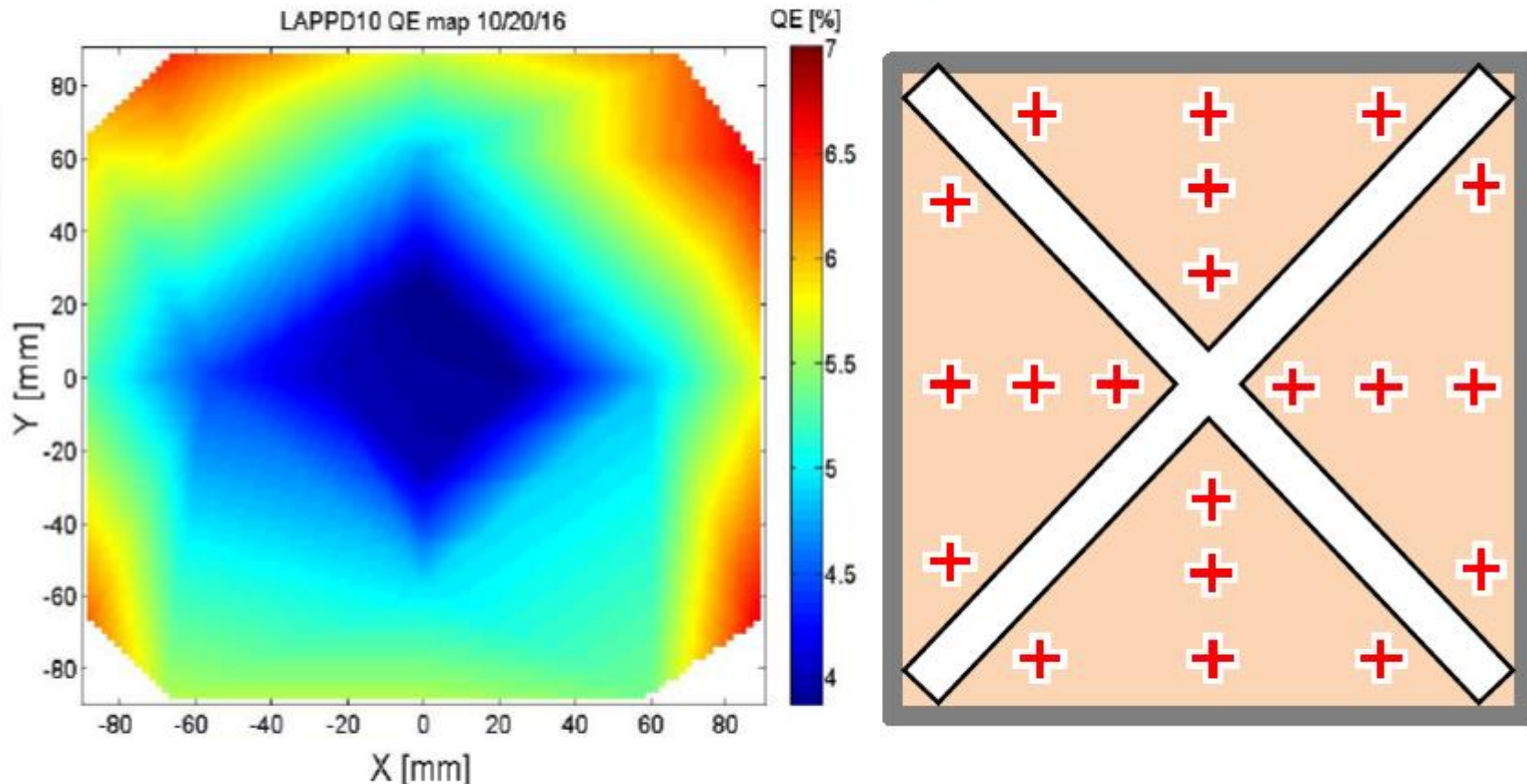
LAPPD #10 QE @ Various Locations, 10/17 @ STP



- Center QE is lower vs. edges,
- Bigger variation at short wavelengths Suggests \gg Sb center thickness.
- QE (range) @365nm = (4.2 % - 6.5%)
- QE (Avg) @365nm = 5.35%

Commercialization Status

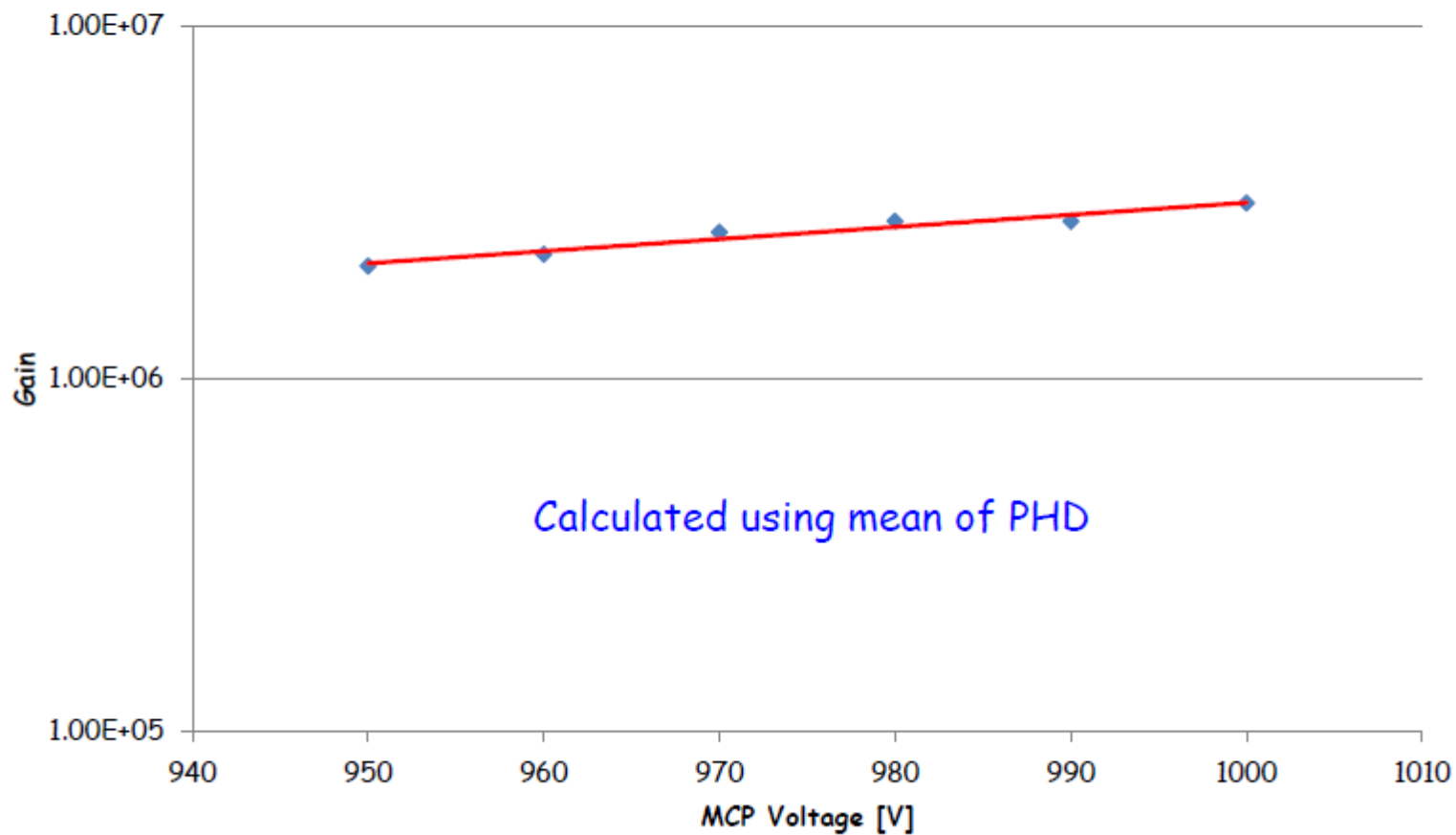
LAPPD #10 QE map @ 365nm



Commercialization Status

LAPPD #10 - Gain

3.16×10^6 @ 1,000V



Commercialization Status

LAPPD # 10 - Status and Conclusions

- Breakthrough! First demonstration of fully functional LAPPD!
- World largest flat panel MCP-PMTs with bi-alkali photocathode
- No detectable leaks since sealing 10/11/2016
- Stable operation at a gain of 3×10^6 → single photon sensitivity
- QE ~ 5.5%, aiming at >20% in future devices
- Remarkably low noise ~12Hz @ 1000V across MCPs with 50mV threshold after preamp
- A transition from pilot production "commissioning" to "exploitation stage" and routine fabrication of detector tiles is expected shortly!
- Incom is on plan to deliver prototype "all glass" LAPPDs in QIV 2016
- Advanced LAPPD Development targets application specific needs, and reduced cost

Commercialization Status

Incom LAPPD Price?

Current pricing is intended to provide cost recovery for unfunded R&D expenses.

Grant money helps offset some of these costs, making LAPPD™ available at a reduced cost for promising early adopter applications.

Incom is committed to working with early adopters to insure that LAPPD can be evaluated for appropriate applications and not allowing cost to be a barrier for that assessment.

Current process technology is scalable, and pending design changes are expected to significantly streamline fabrication and further reduce manufacturing costs.

In a recently awarded DOE GEN II LAPPD grant, Incom Inc. projected a unit cost of \$10,000 each, with high volume (1,000 units) orders.

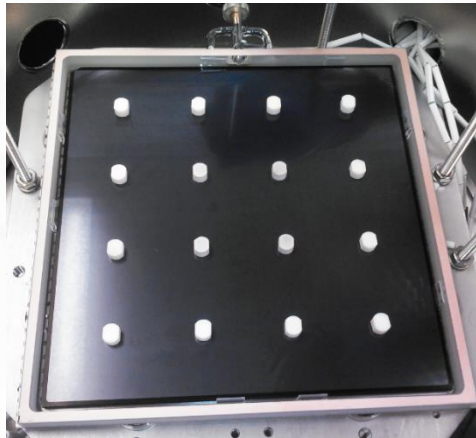
Commercialization Status



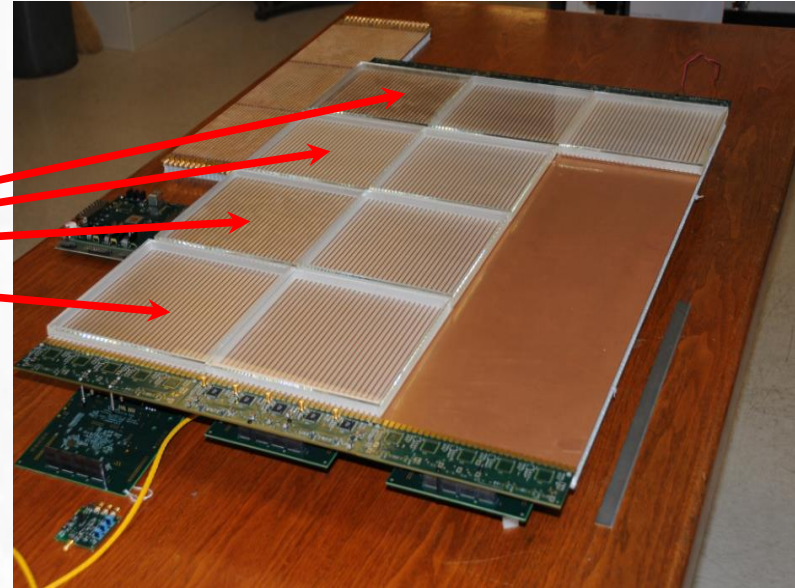
Goal of the R&D Effort at UChicago

Affordable large-area many-pixel photo-detector systems
with picosecond time resolution

LAPPD module 20x20 cm



Example of a Super Module



A production rate of **50 LAPPDs/week**
would deliver 20,000 LAPPDs in ~7.5 years

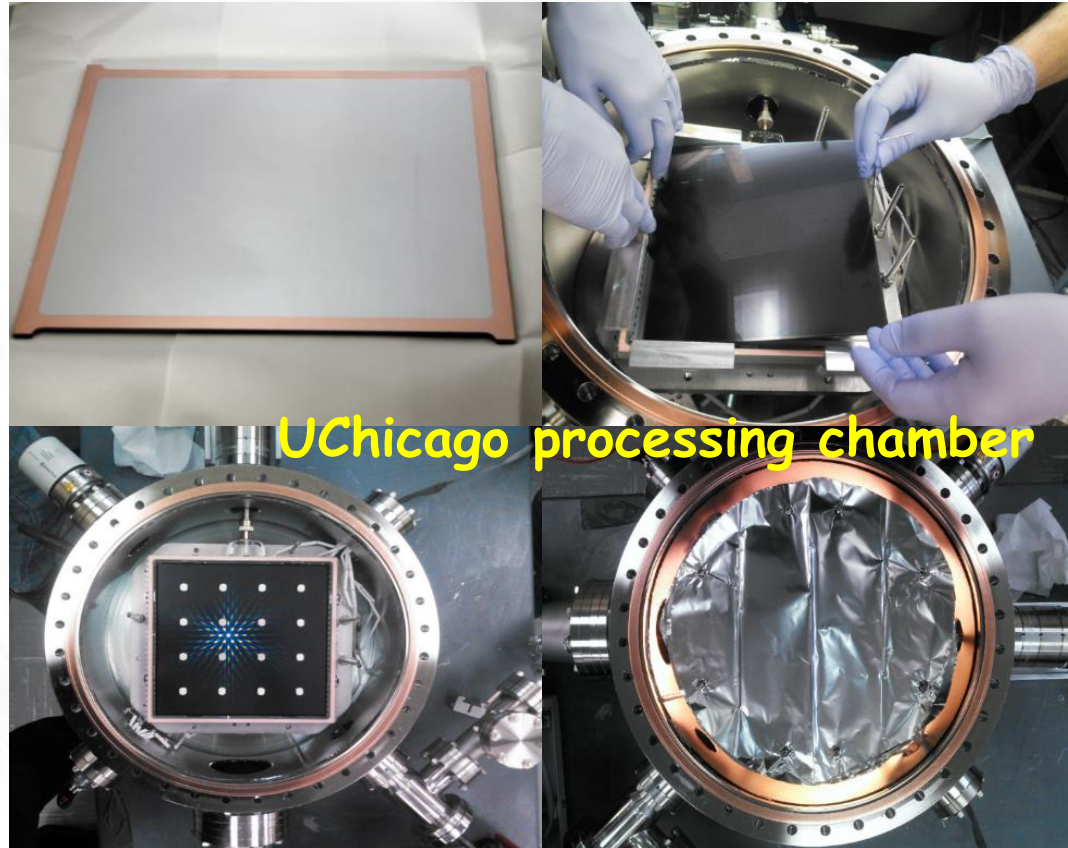
- High volume production can be challenging
- We are exploring if a non-vacuum transfer process can be inexpensive and easier for a very high volume production

UChicago goal is to enable high volume production
at Incom so we can do physics using LAPPD™

In-Situ Assembly Strategy

Simplify the assembly process by avoiding vacuum transfer:

make photo-cathode after the top seal
(PMT-like batch production)



Heat only the tile
not the vacuum vessel

Intended for
parallelization

- Step 1:** pre-deposit Sb on the top window prior to assembly
- Step 2:** pre-assemble MCP stack in the tile-base
- Step 3:** do top seal and bake in the same heat cycle
using dual vacuum system
- Step 4:** bring alkali vapors inside the tile to make photo-cathode
- Step 5:** flame seal the glass tube or crimp the copper tube

In-Situ Assembly Facility UChicago

The idea is to achieve volume production by operating many small-size vacuum processing chambers at the same time



Looking forward towards transferring
the in-situ process to industry

In-Situ Process Pre-requisite

Reliable hermetic seal over a 90-cm long perimeter

Input: Indium Solder Flat Seal Recipe

- Two glass parts with flat contact surfaces

Process:

- Coat 200 nm of NiCr and 200 nm of Cu on each contact surface (adapted from seals by O.Siegmund at SSL UC Berkeley)
- Make a sandwich with indium wire
- Bake in vacuum at 250-300C for 24hrs

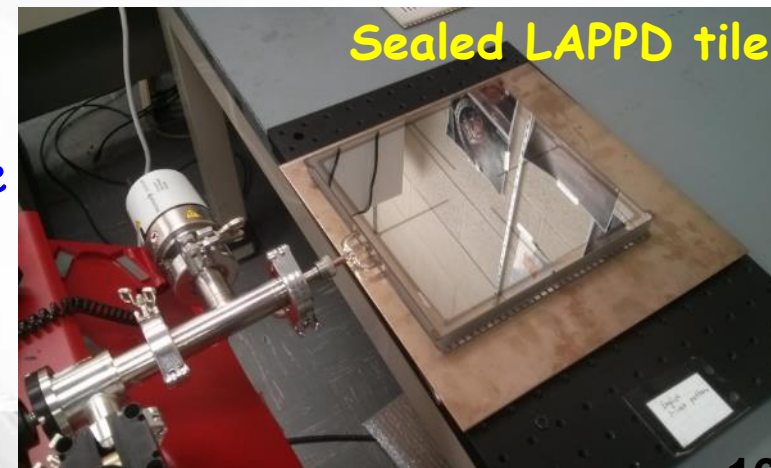
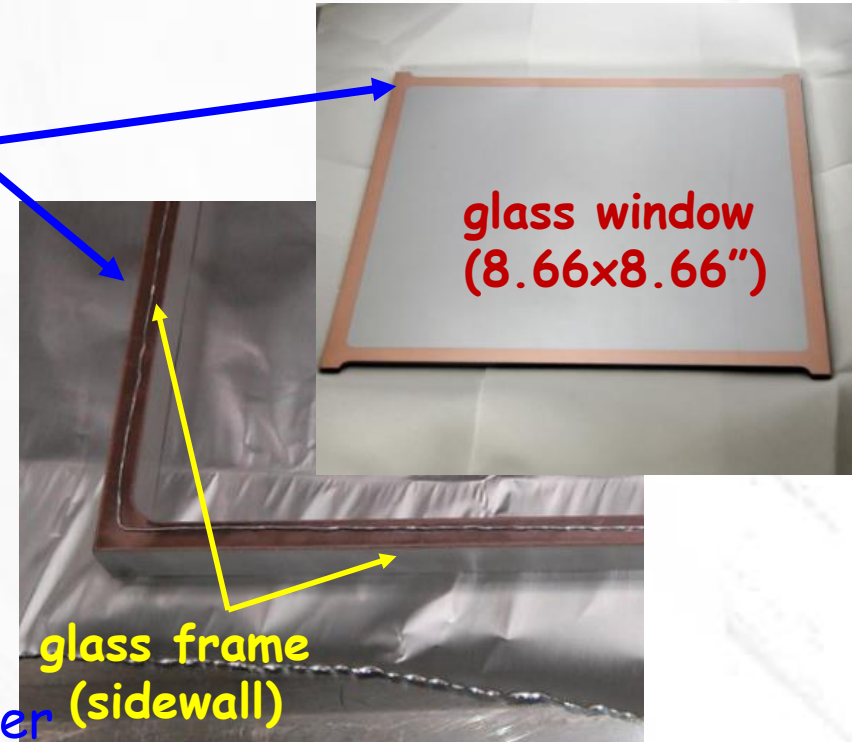
Key features:

- A good compression over the entire perimeter is needed to compensate for non-flatness and to ensure a good contact
- In good seals indium penetrates through entire NiCr layer (Cu always "dissolves")

This recipe is now understood

It works well over large perimeters

Metallization and compression are critical

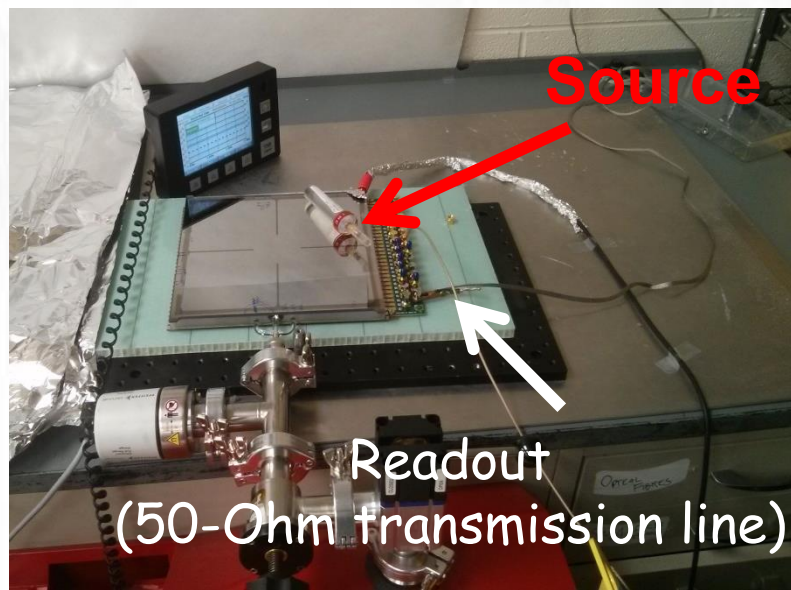


First Signals from an In-Situ LAPPD

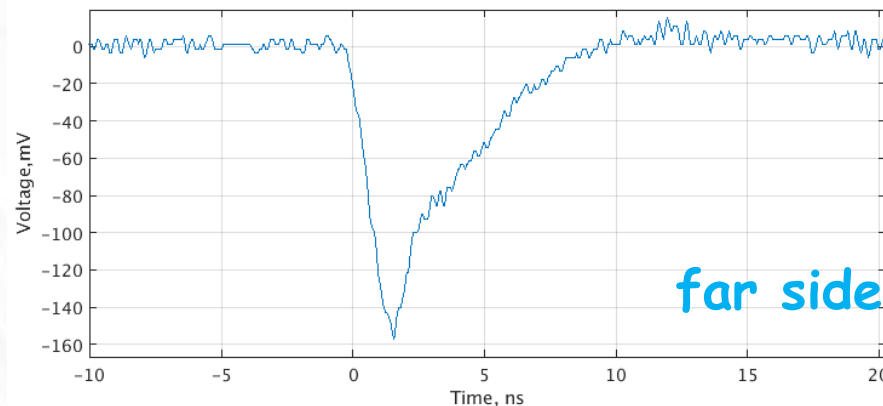
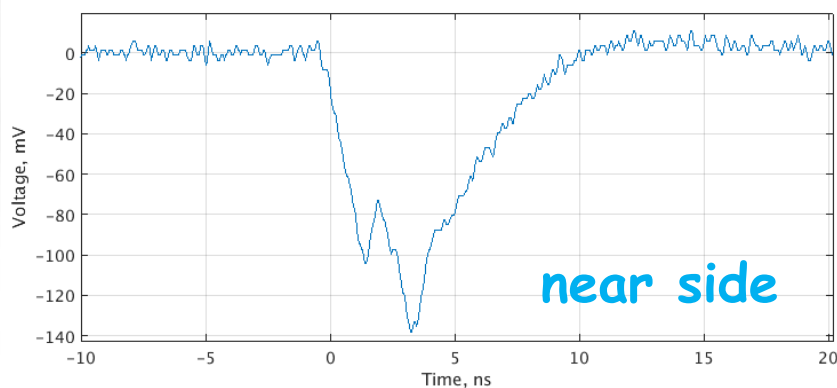
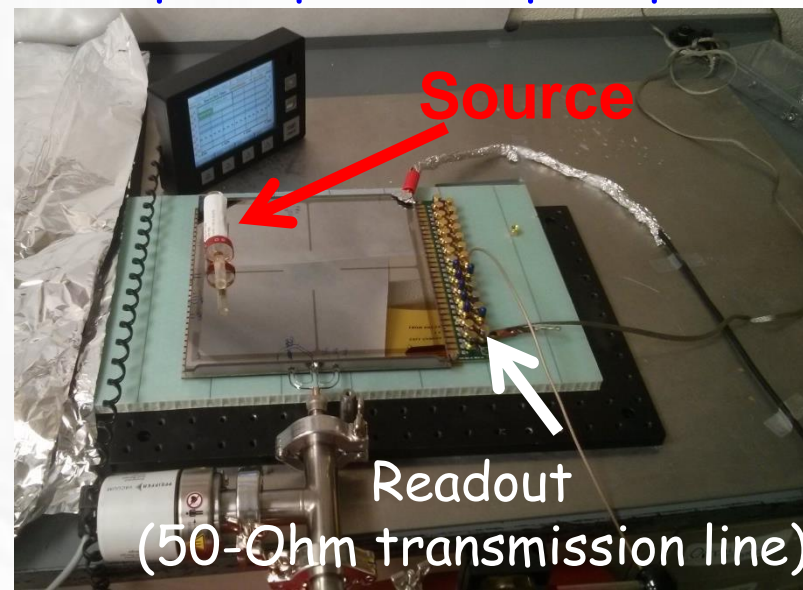
April, 2016

(Sb cathode)

Near side: reflection from unterminated far end



Far side: reflection is superimposed on prompt

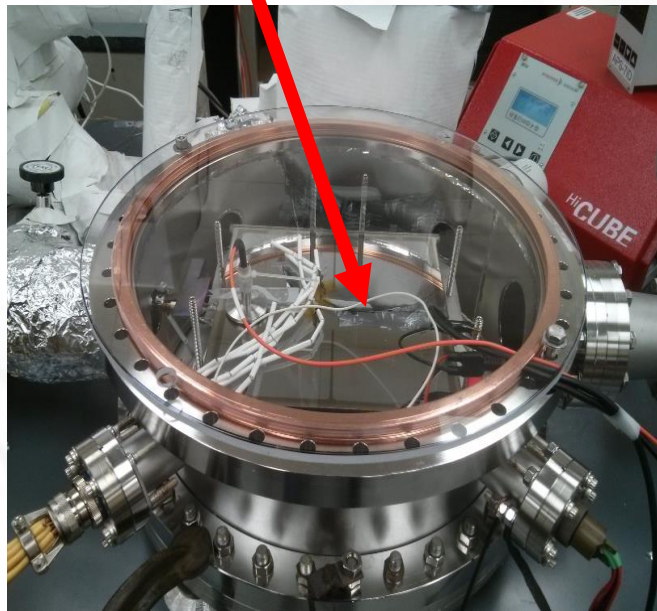


The tile is accessible for QC before photo-cathode shot
Could help the production yield

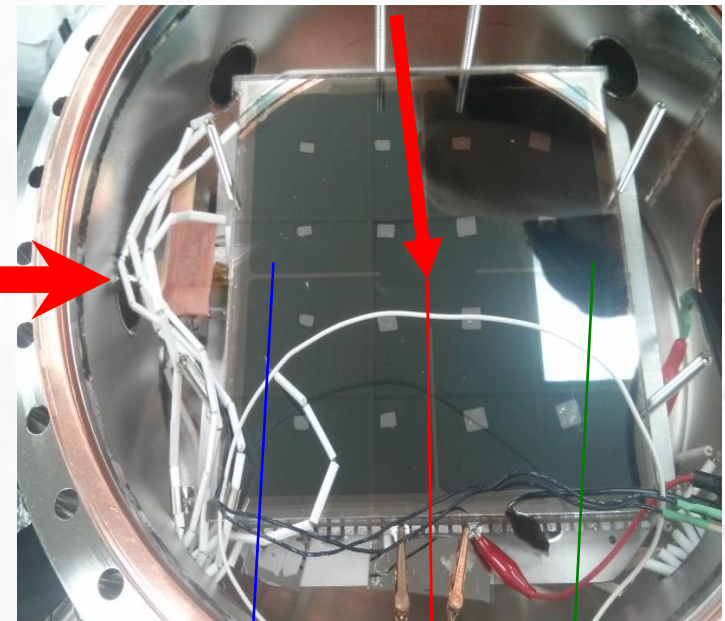
In-Situ Photo-Cathode

July, 2016

Sb layer only



Cs-Sb photo-cathode

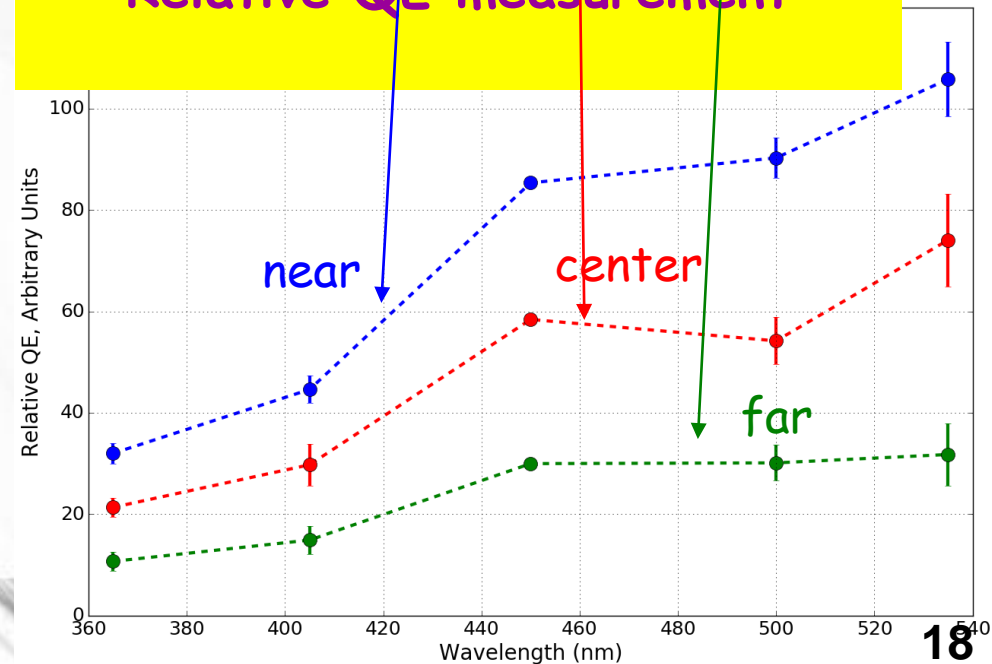


- First in-situ commissioning run (Summer 2016)
- saw the first photo-current response from in-situ photo-cathode
 - measured relative QE (absolute QE is tricky due to DC current through the whole stack)
 - demonstrated a sealed tile configuration
 - no QE drop for 2 weeks after the valve to the pump was closed
 - no QE drop for 3 weeks after flame seal

Note on this commissioning run:

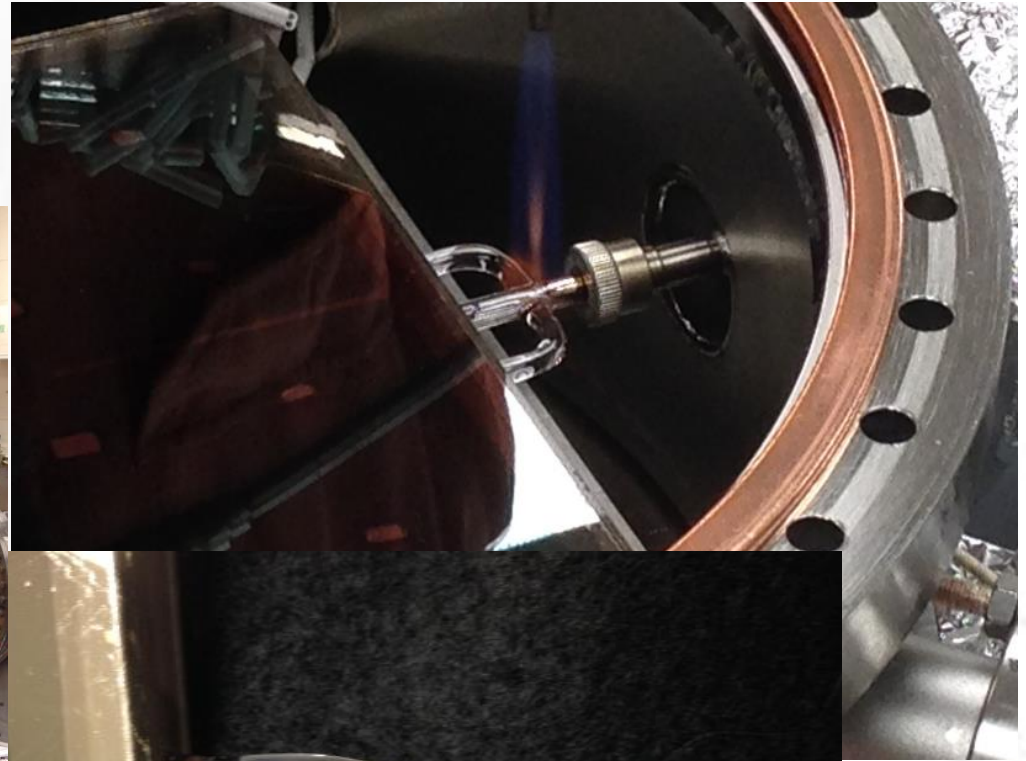
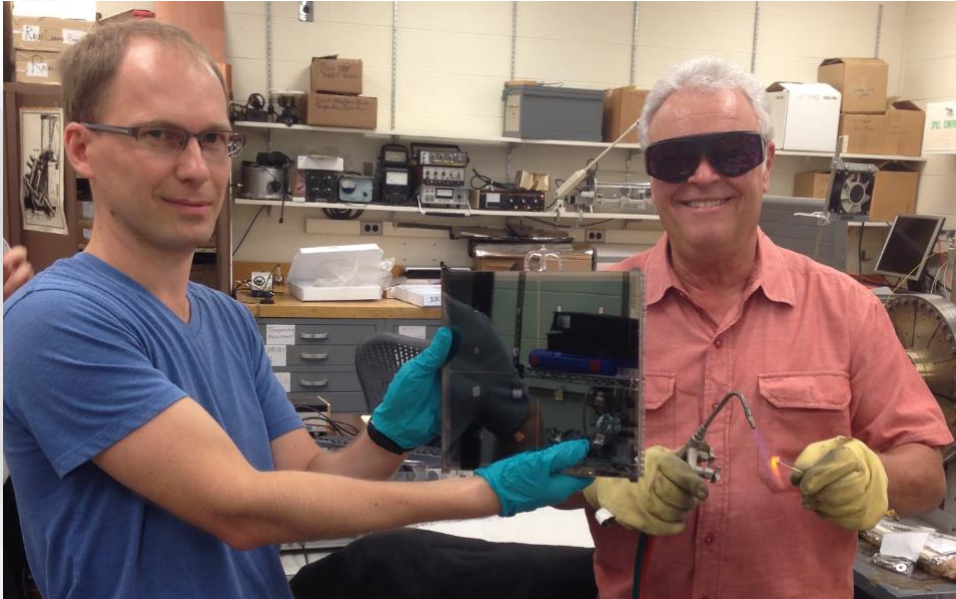
PC is very thick for transmission mode operation (initial 20nm of Sb translates into ~80nm of Cs-Sb)

Relative QE measurement



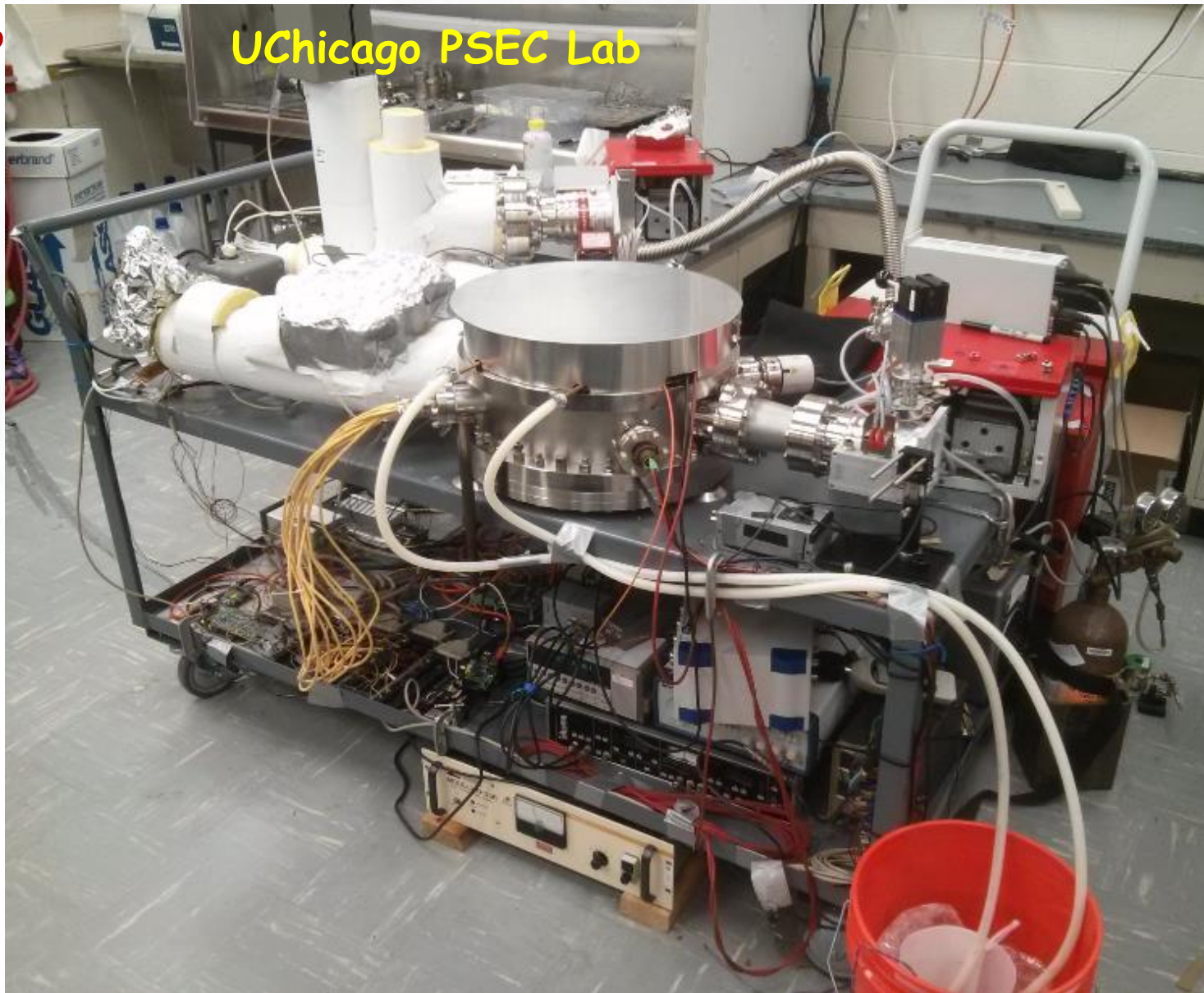
Flame Seal - Final In-Situ Step

August 18, 2016



Current Status of the In-Situ

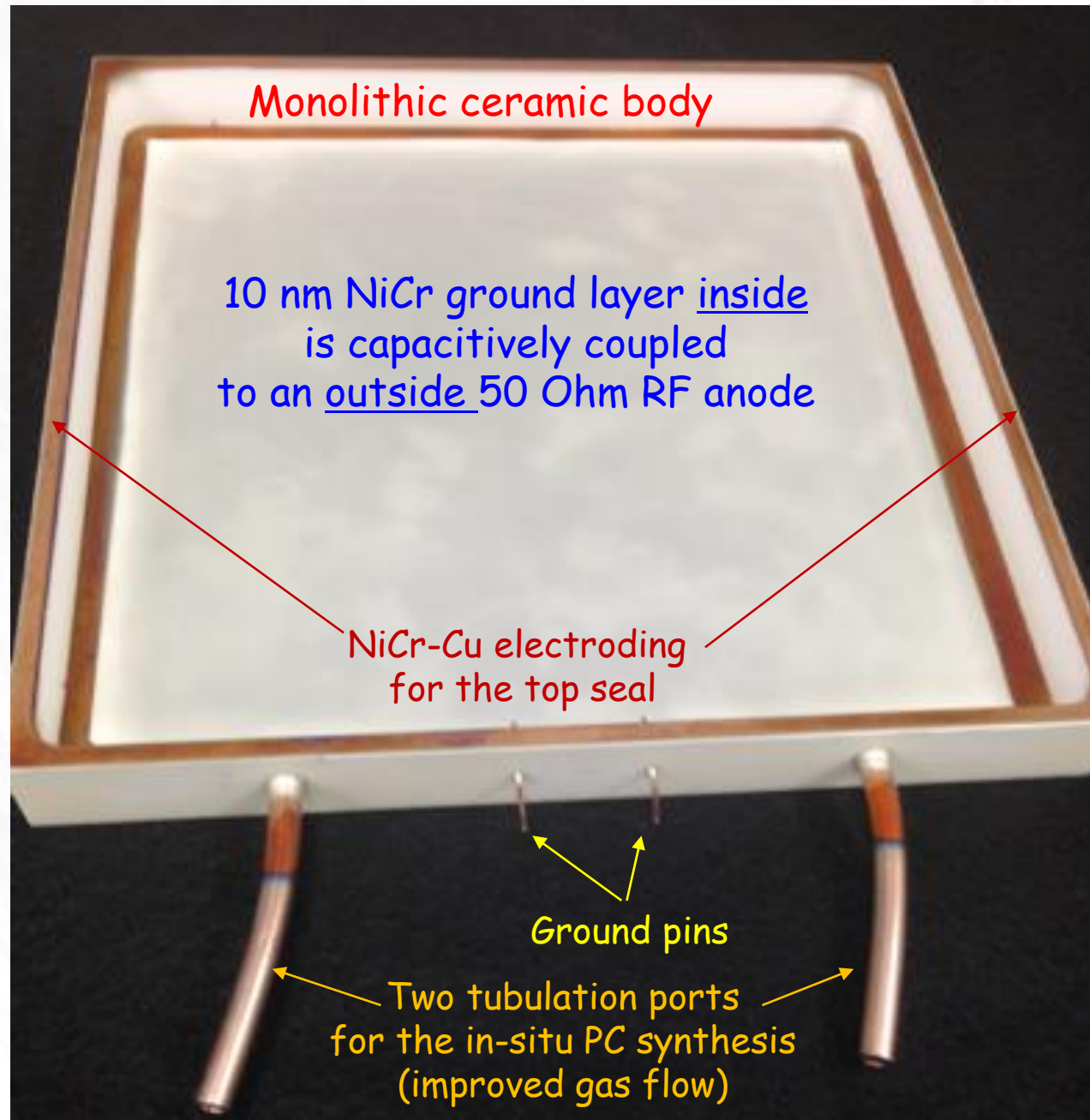
October, 2016



Improved instrumentation for process control
(Hard work by Evan Angelico and Eric Spieglan)

Gen-II LAPPD

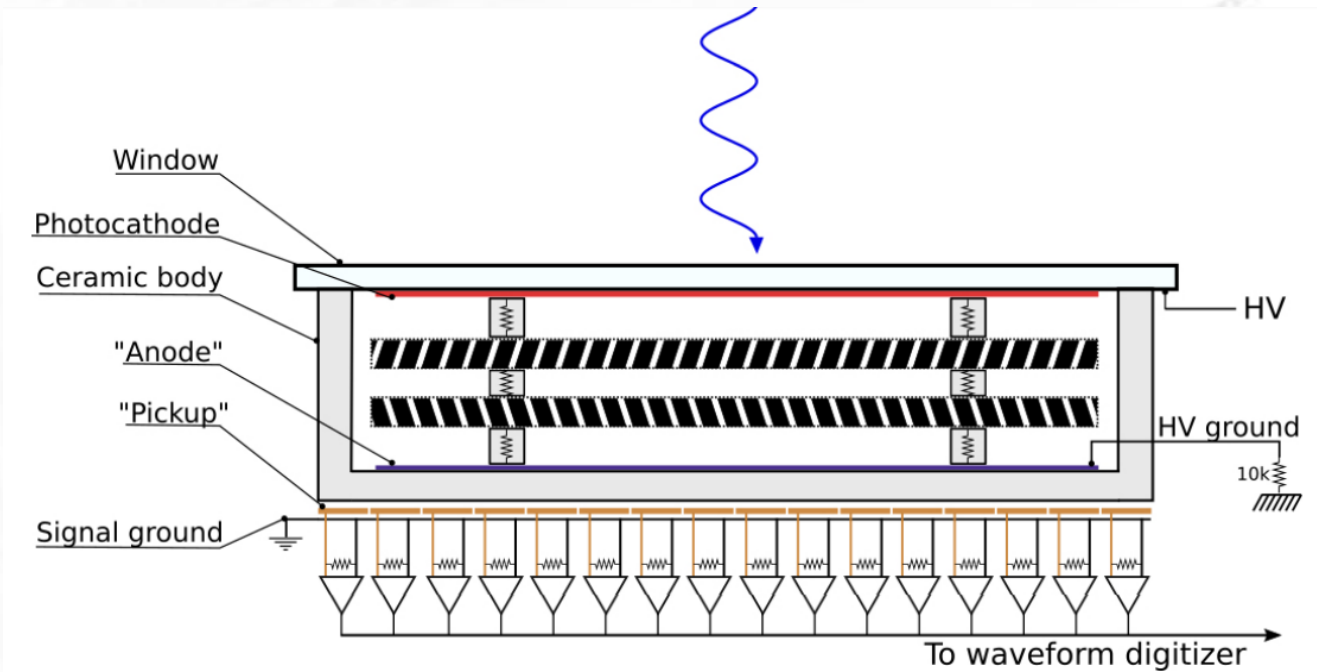
- Robust ceramic body
- Anode is not a part of the vacuum package
- Enables fabrication of a generic tile for different applications
- Compatible with in-situ and vacuum transfer assembly processes



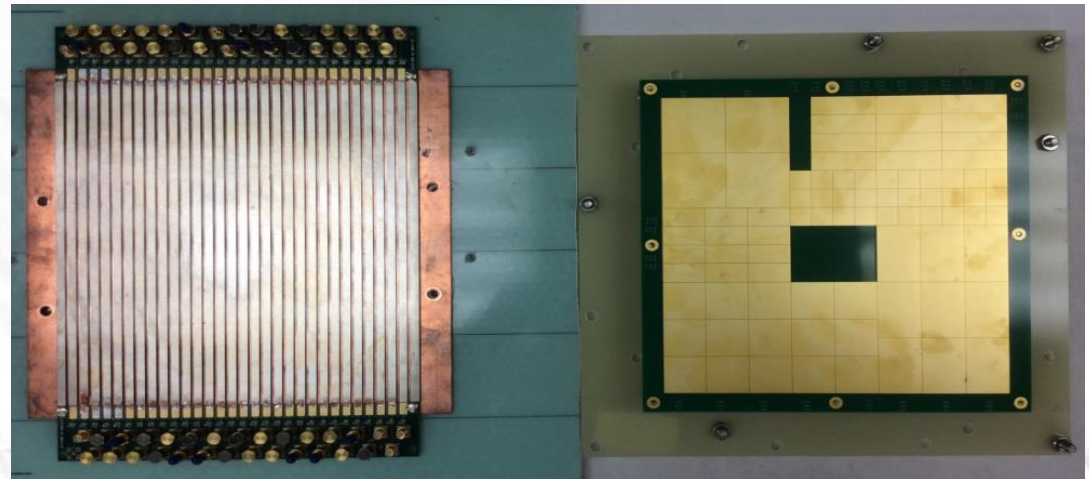
Gen-II LAPPD: "inside-out" anode

Custom anode is outside

Compatible with high rate applications



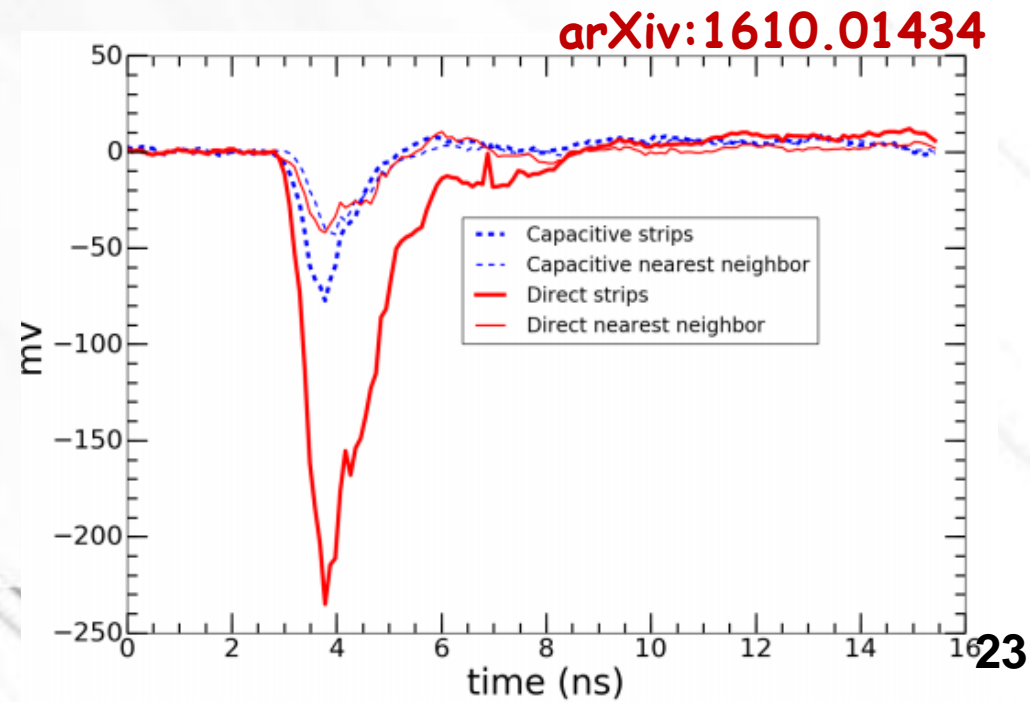
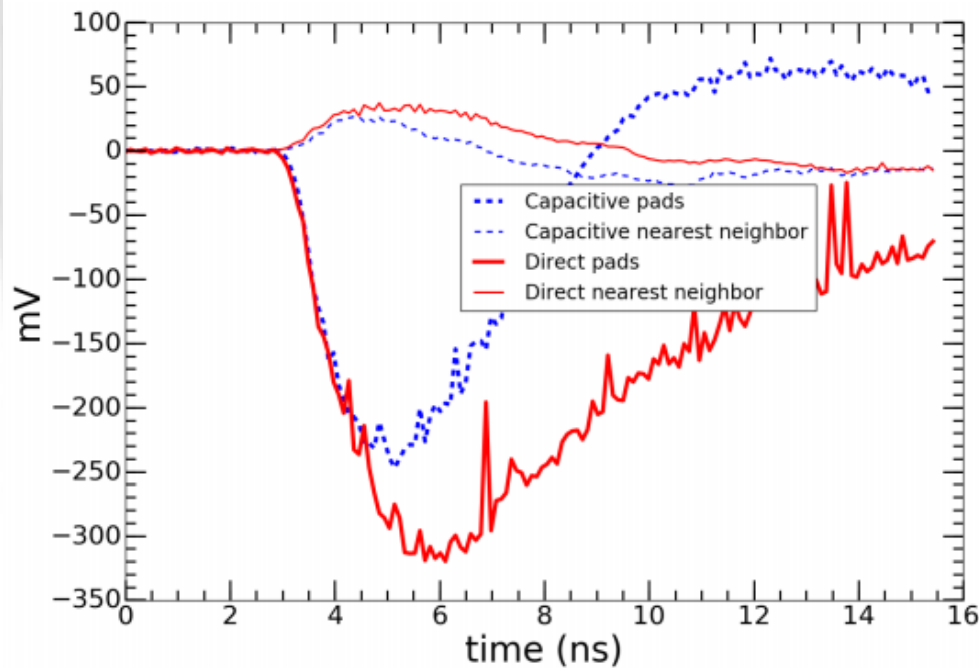
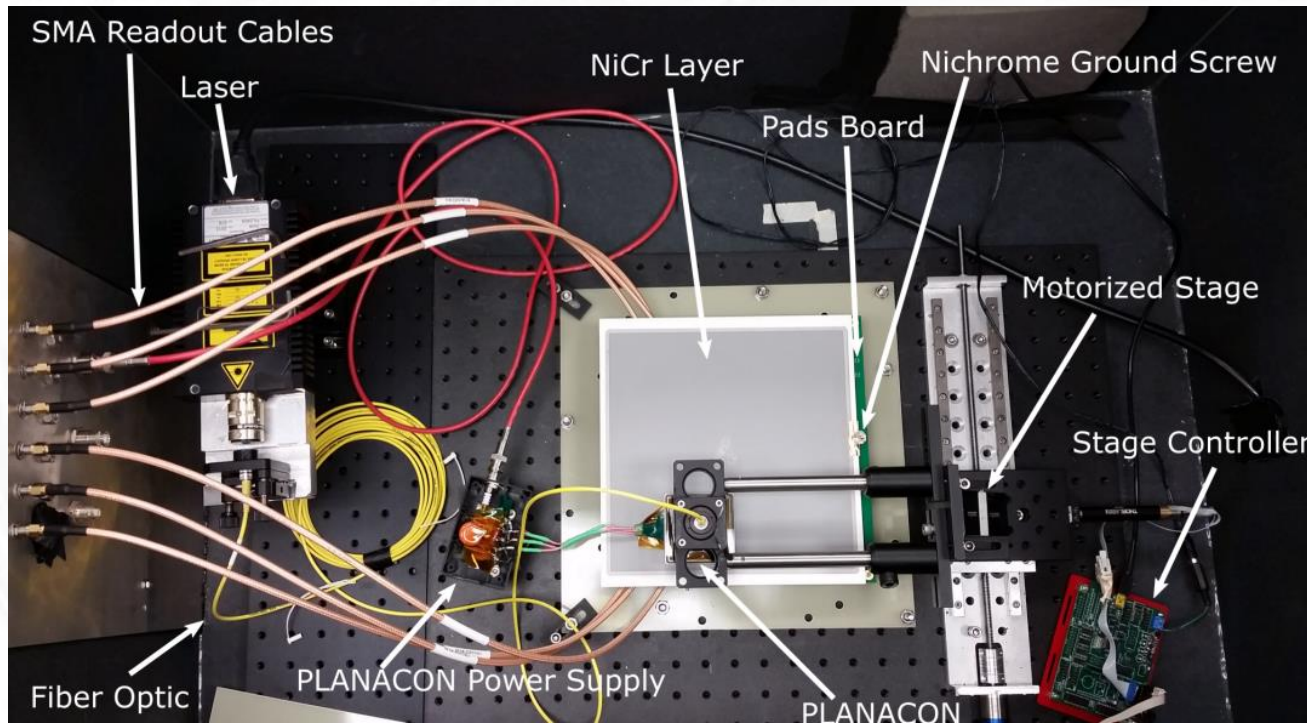
Choose your own readout pattern



For details see
arXiv:1610.01434
(submitted to NIM)

Inside-out Anode Testing

Evan Angelico
And
Todd Seiss



arXiv:1610.01434

Summary

- Commercialization at Incom Inc. goes well
- They would like to keep close contact with early adopters
- With the goal to use LAPPDs in large experiments
UChicago group is focused on R&D for high volume production process
- Making photo-cathode in-situ as a final step is very attractive
 - leak check before PC-synthesis
 - real-time tuning and optimization of PC is possible
- Right at the moment we are working on photo-cathode optimization and Gen-II LAPPD vacuum packaging

Back-up

The 2013 Transition from LAPPD to Production: The 4 Parallel Paths

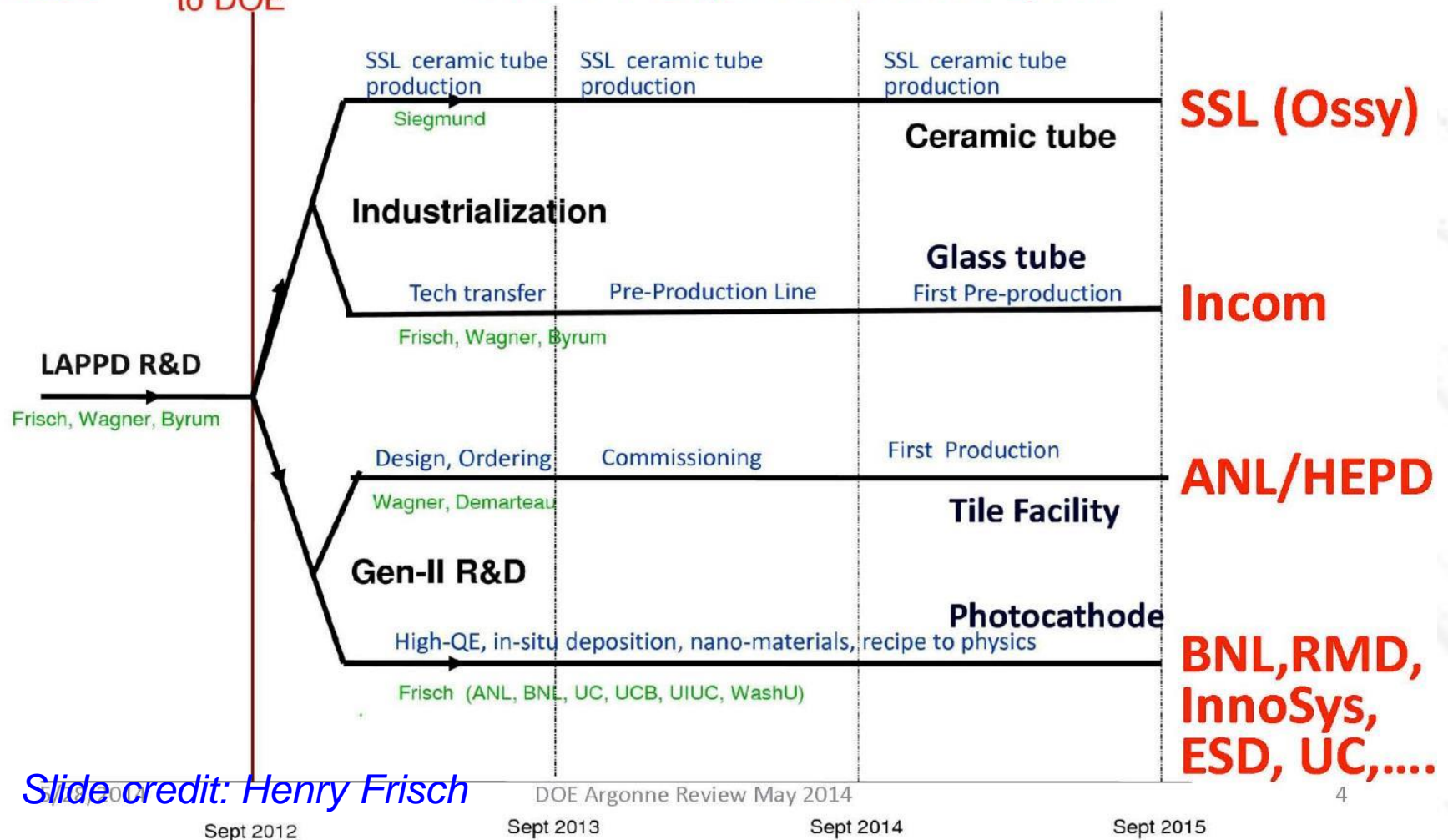
Dec 12, 2012 Presentation to DOE

(a UC view)

R&D

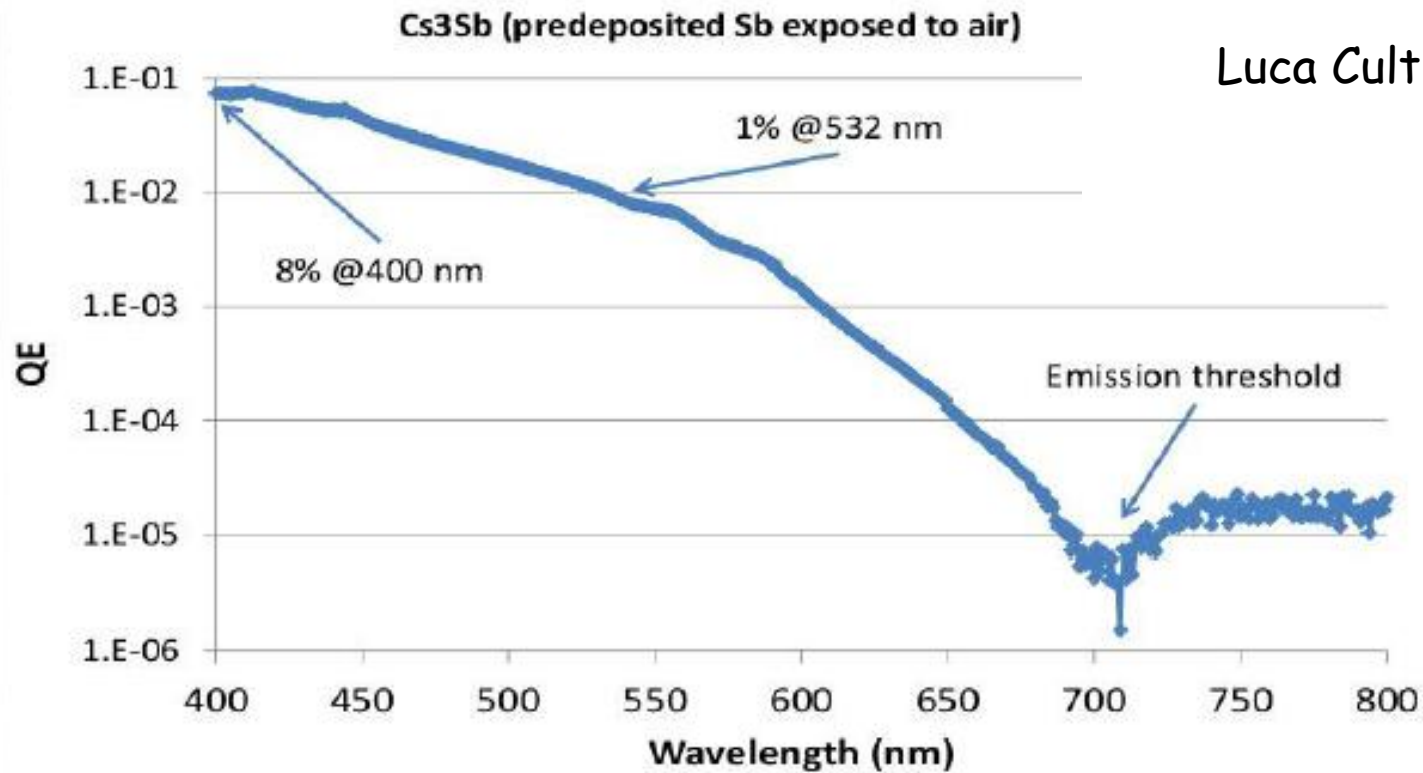
Presentation to DOE

LAPPD Pre-production Project



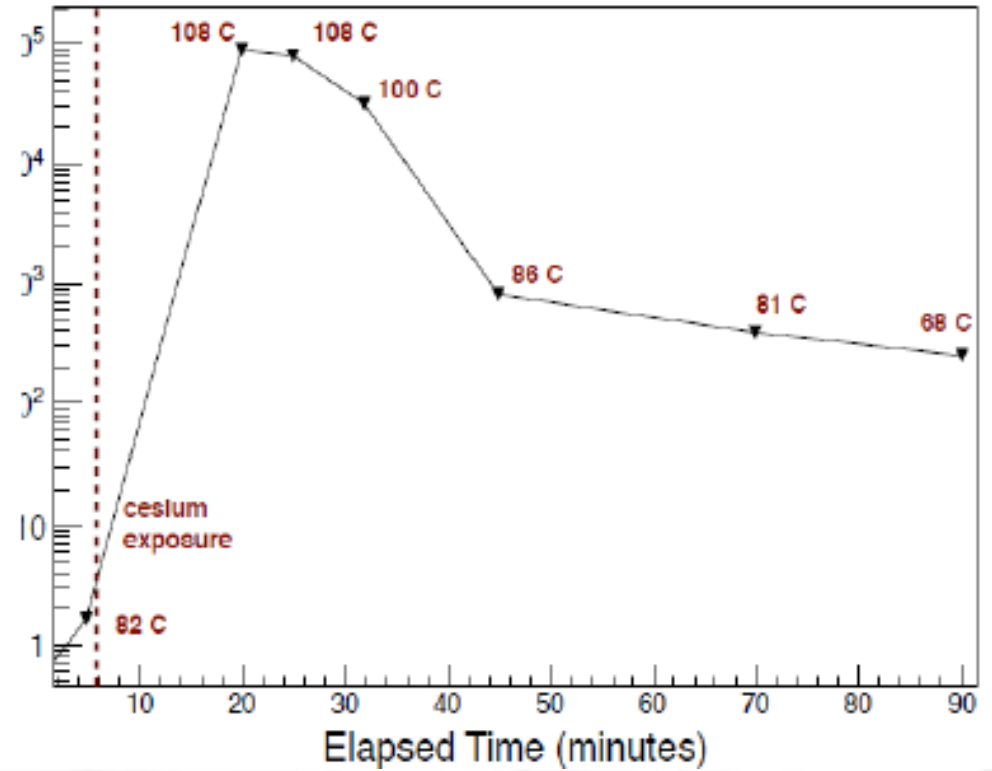
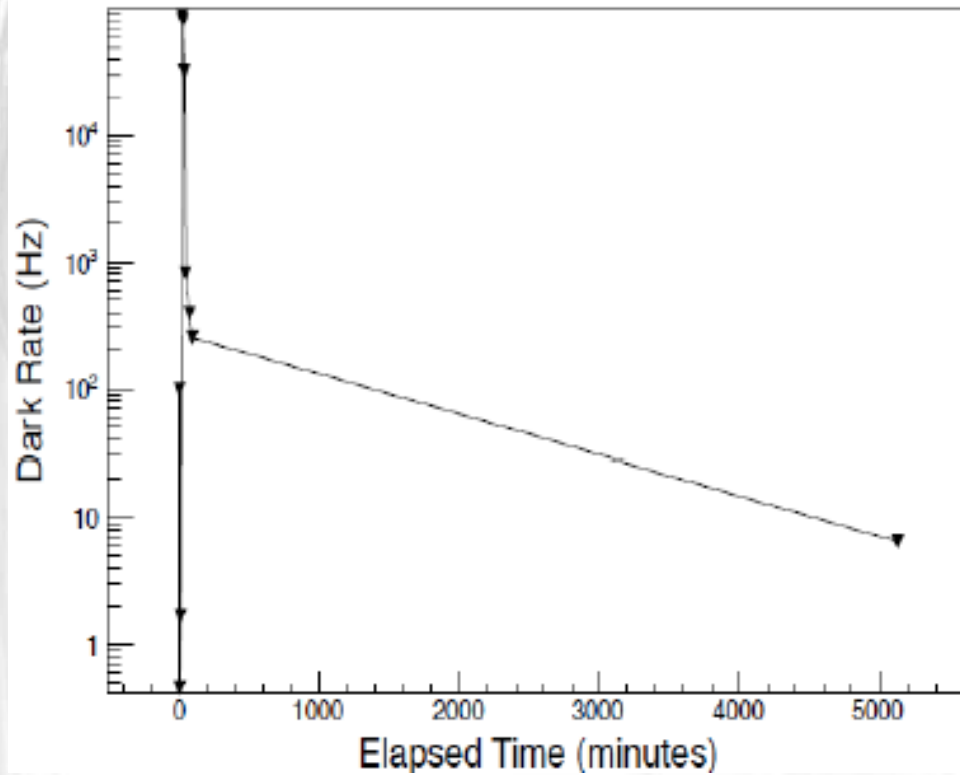
Slide credit: Henry Frisch

Can you make PC after Sb was exposed to air?



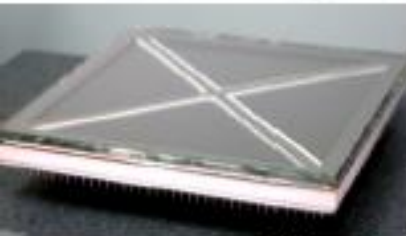
What about noise in the MCPs after Cs-ation?

Matt Wetstein

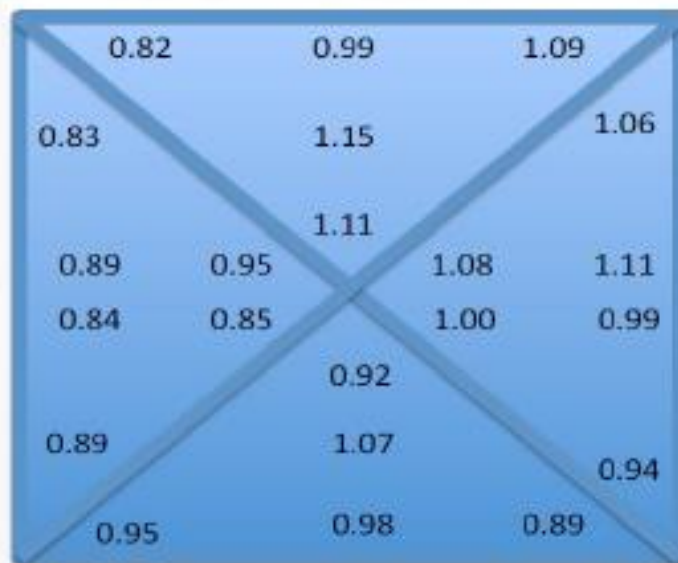
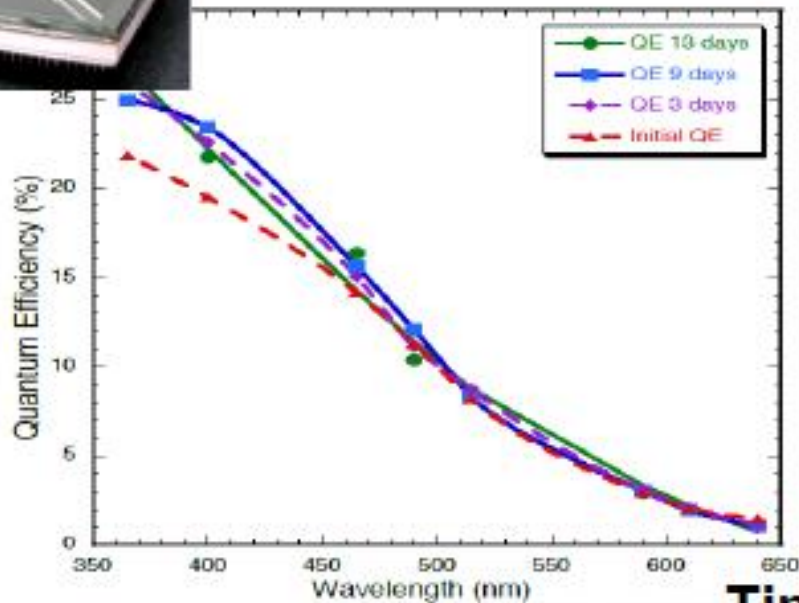


SSL Ceramic LAPPD Tile Results

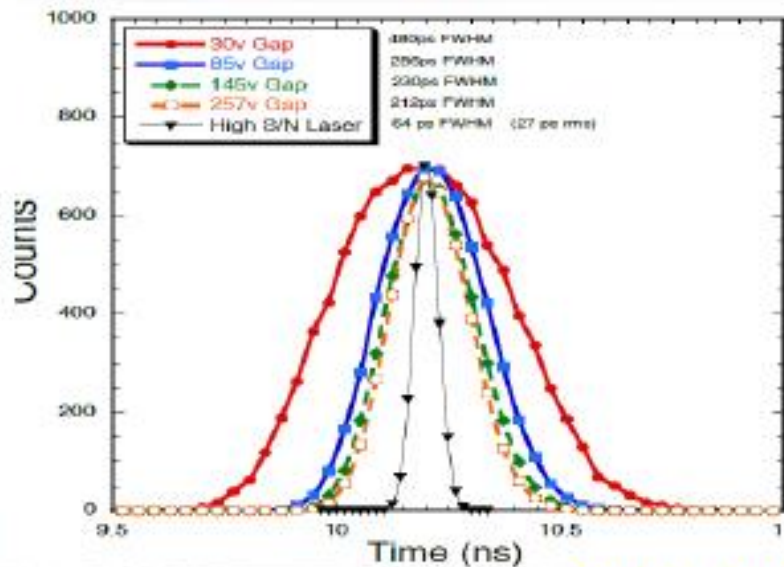
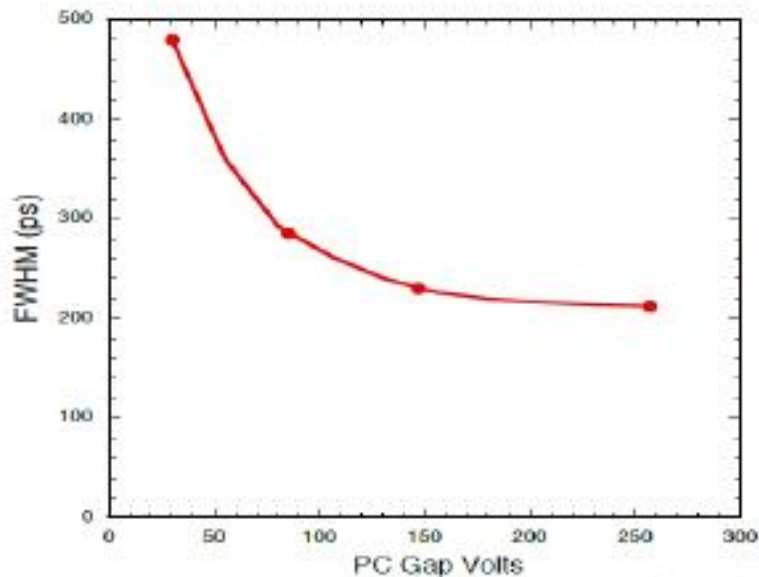
Measurements after full processing cycle inside the vacuum chamber



QE



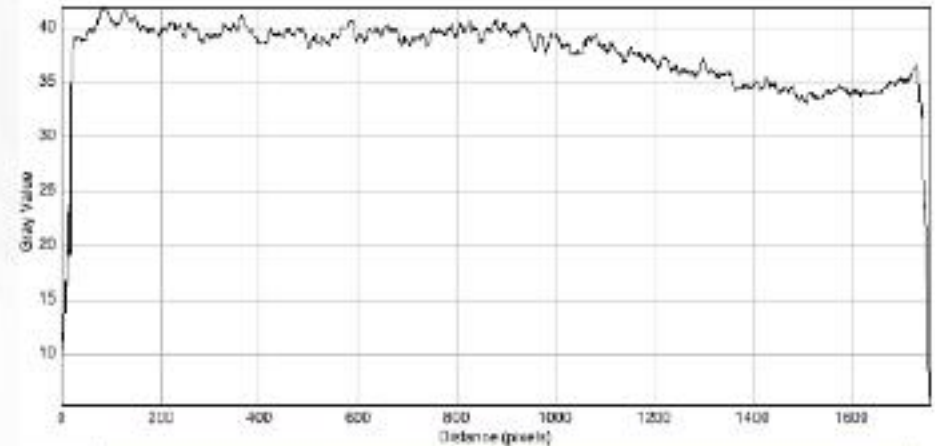
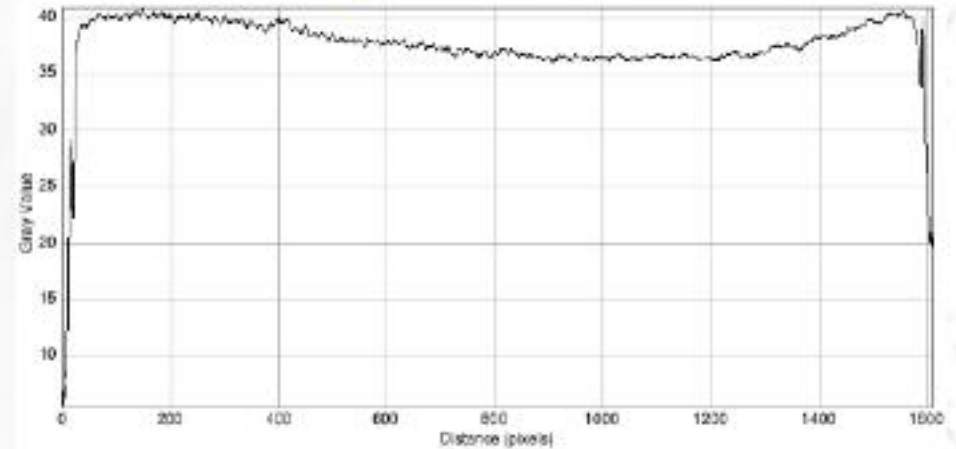
Timing



Gain Uniformity



Gain map image for a pair of 20 μm pore, 60:1 L/D, ALD borosilicate MCPs, 950 V per MCP, 184 nm UV



Gain is uniform within $\sim 15\%$
across full 20 x 20 cm^2 area

O.H.W. Siegmund, N. Richner, G. Gunjala, J.B. McPhate, A.S. Tremsin, H.J. Frisch, J. Elam, A. Mane, R. Wagner, C.A. Craven, M.J. Minot, "Performance Characteristics of Atomic Layer Functionalized Microchannel Plates" Proc. SPIE 8859-34, in press (2013).

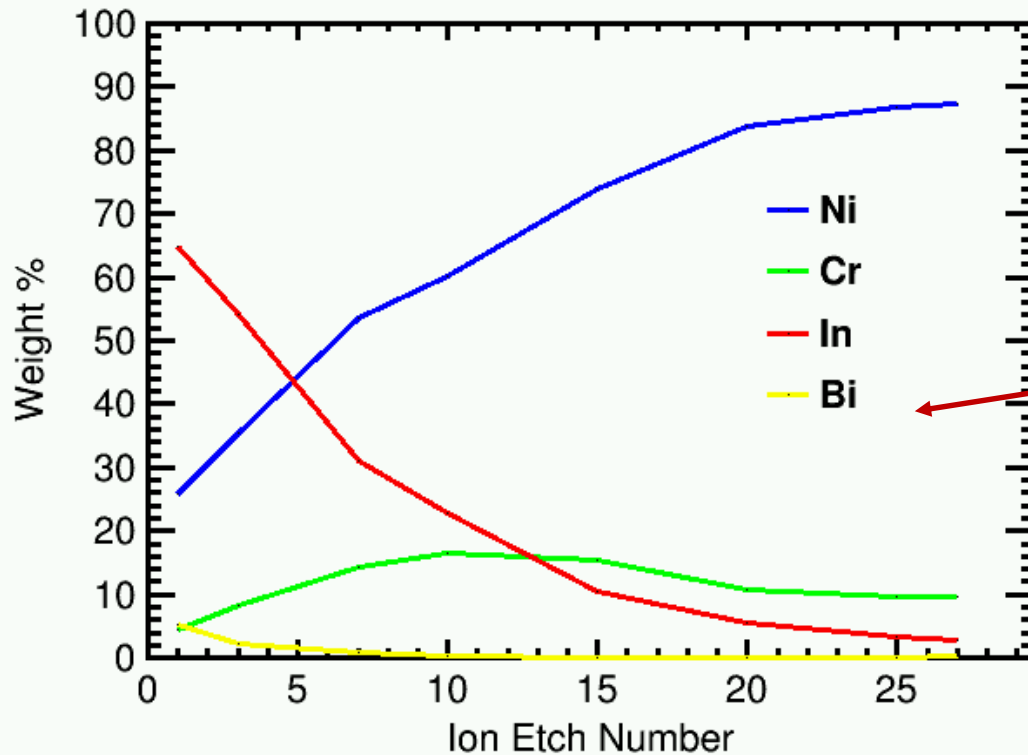
Noise $< 0.1 \text{ counts cm}^{-2} \text{ s}^{-1}$

Metallurgy of the Seal

Moderate temperatures and short exposure time:

- A thin layer of copper quickly dissolves in molten indium
 - Indium diffuses into the NiCr layer

Depth profile XPS



Layer depth (uncalibrated)

Low melting InBi alloy allows to explore temperatures below melting of pure In (157C)

Glass with NiCr-Cu metallization exposed to InBi at ~100C for <1hrs (it seals at these conditions)



InBi was scraped when still above melting (72C)

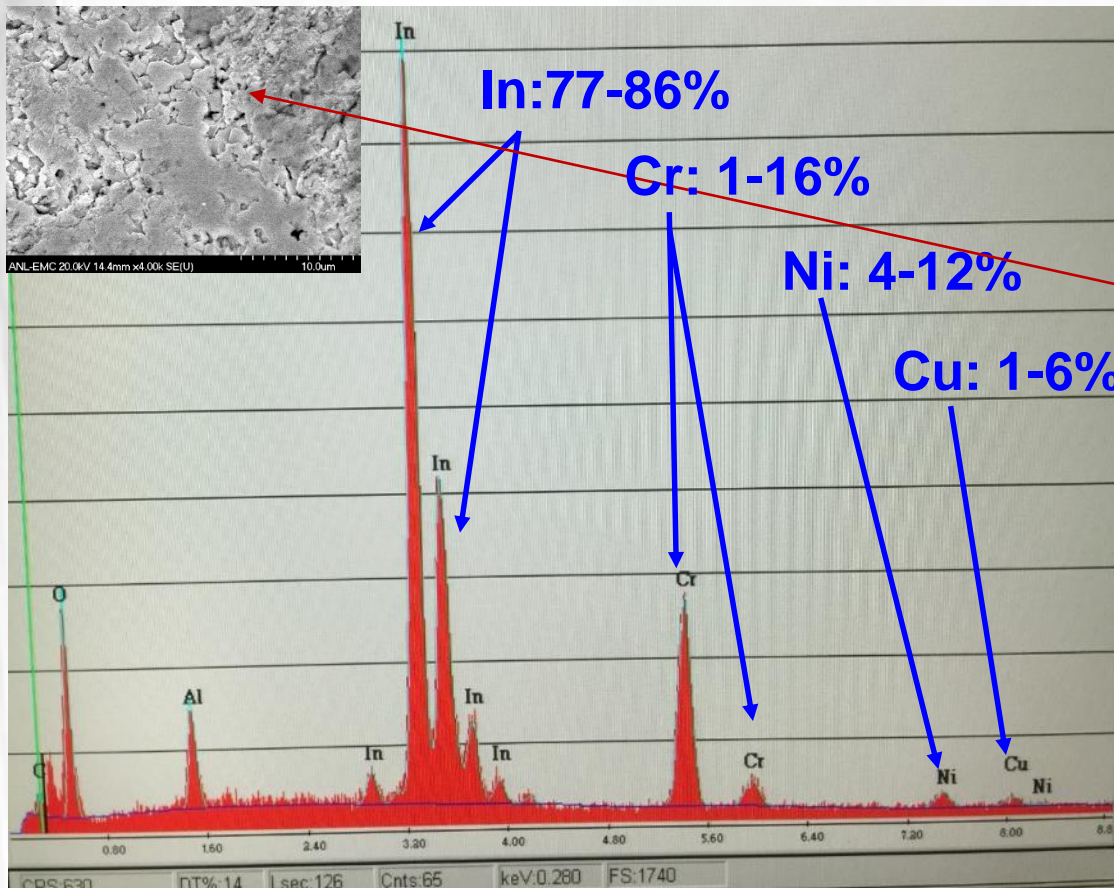
The ion etch number is a measure for the depth of each XPS run

XPS access courtesy of J. Kurley and A. Filatov at UChicago

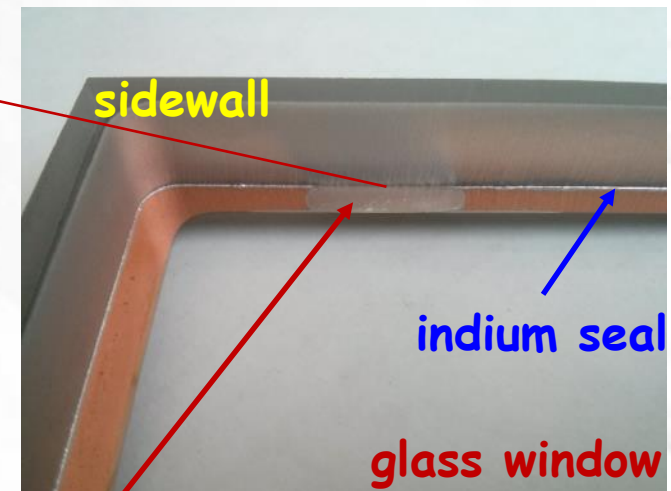
Metallurgy of the Seal

- High temperatures and long exposure time
- Indium penetrates through entire NiCr layer

SEM and EDAX of the metal surface scraped at the interface



Glass with NiCr-Cu metallization bonded by **pure In** at ~250C for 2hrs (it seals at these conditions)



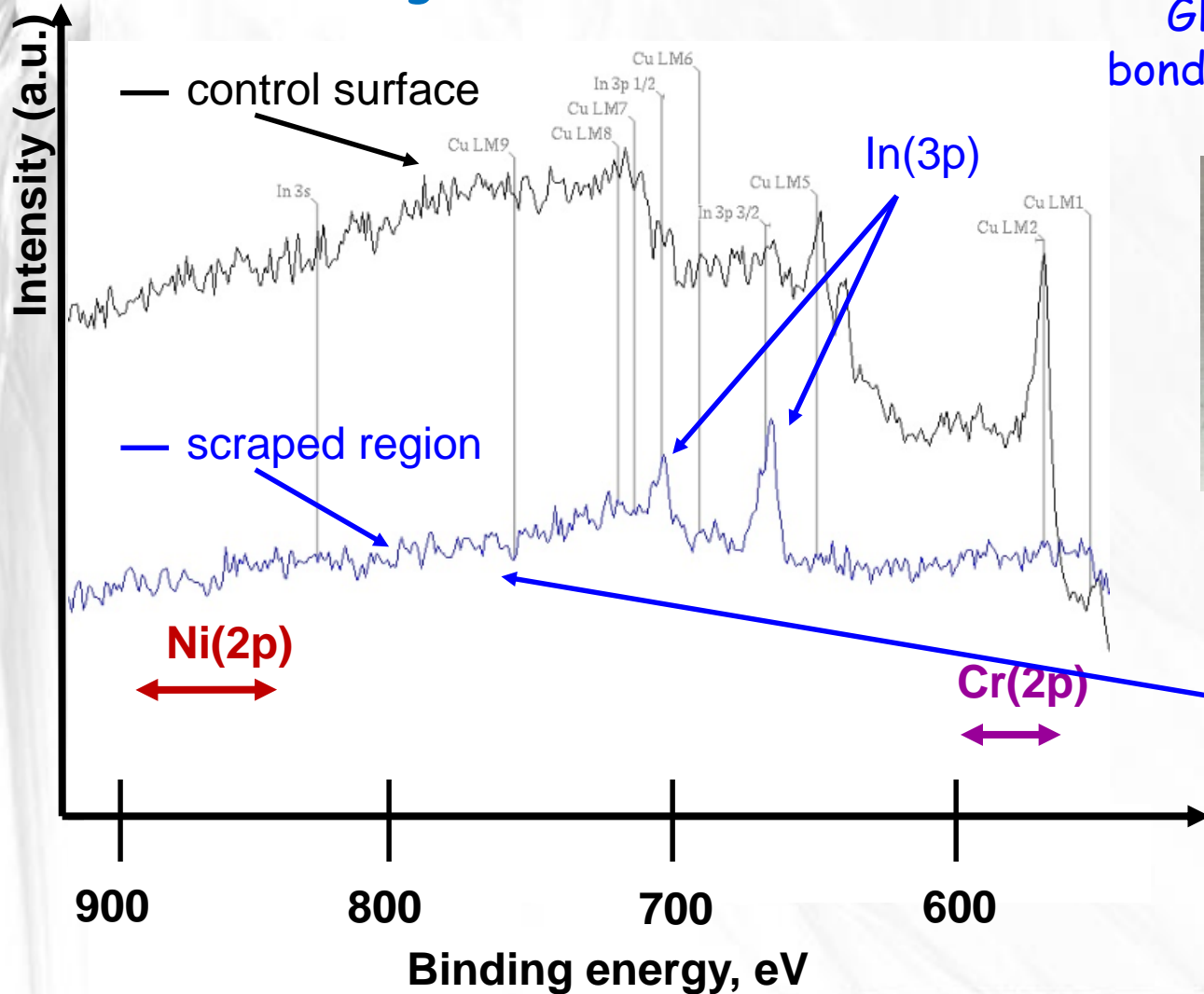
Cut and scrape at the metal-glass interface

Metallurgy of a Good Seal

Higher temperatures and longer exposure time

- Indium penetrates through entire NiCr layer

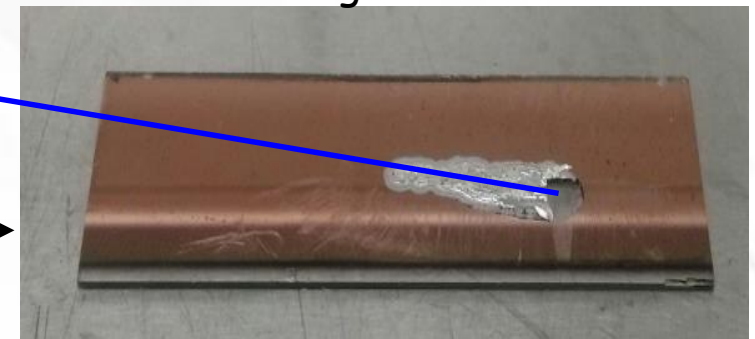
XPS of the glass side of the interface



Glass with NiCr-Cu metallization bonded by **pure In** at **~350C** for **24hrs** (it seals at these conditions)



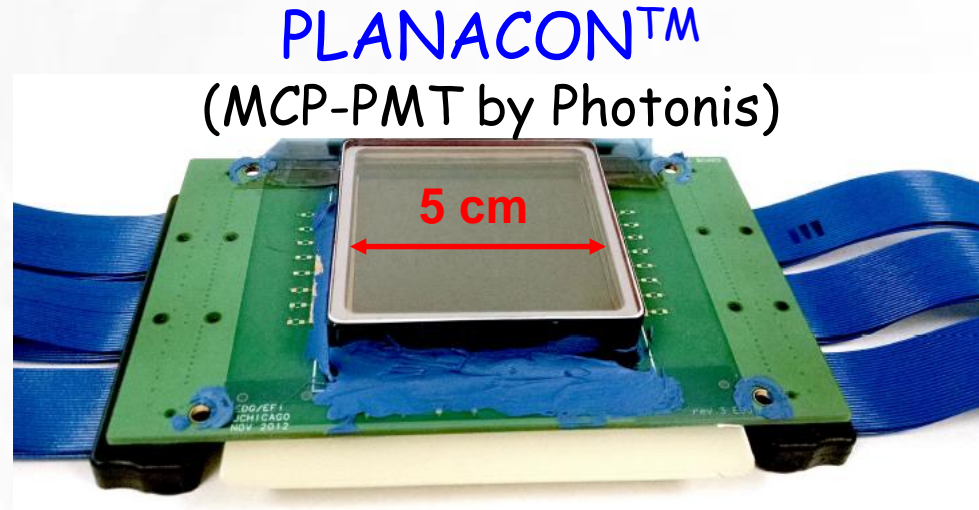
Cut and scrape at the metal-glass interface



We now reliably seal at **250-300C** for **12-24hrs**

Indium seal recipes exist for a long time

We adapted NiCr-Cu scheme
from O.Siegmund at SSL UC Berkeley



Why do we need another indium seal recipe?

Make larger photo-detectors

Our recipe scales well to large perimeter

Simplify the assembly process

Our recipe is compatible with PMT-like batch
production